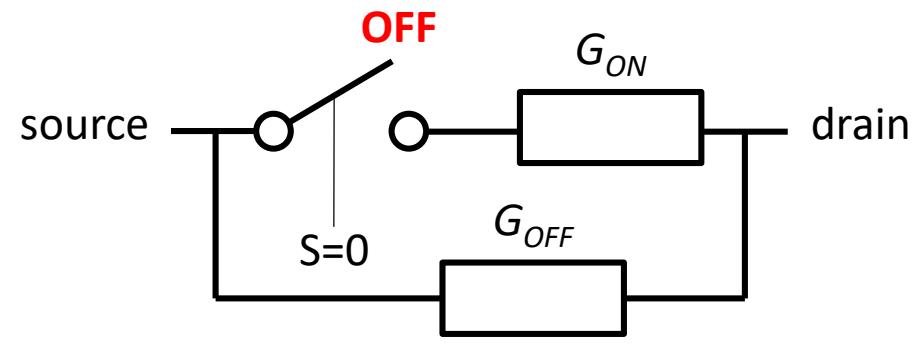
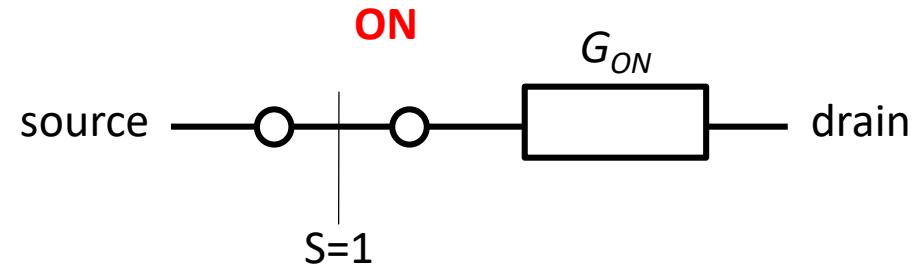


# Lecture 2

## The MOSFET

# The MOSFET as a switch

In the digital world, the MOSFET is a switch that is either **ON** with conductance  $G_{ON}$ , or **OFF** with zero conductance,  $G_{OFF}=0$



# Lecture outline

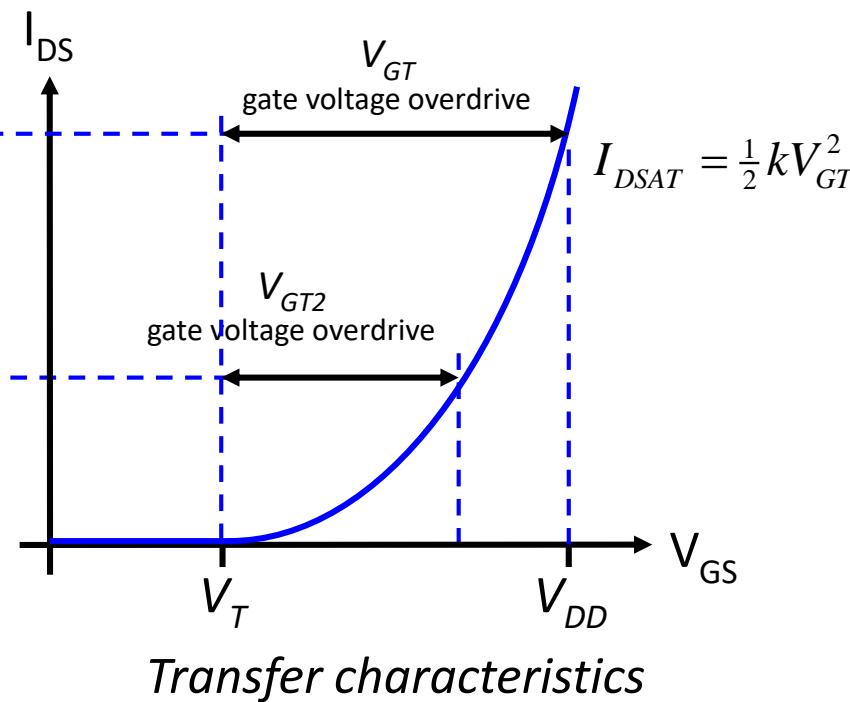
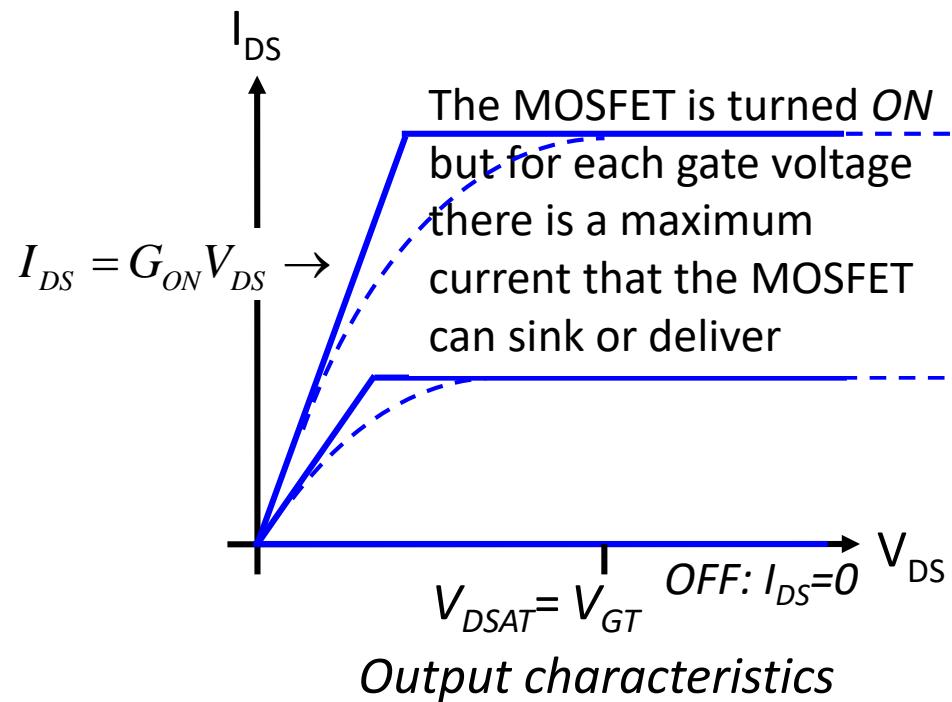
In this lecture we are going to have a closer look at some basic properties of the MOSFET beyond the switch model

- Why?
- Because, even if the switch model is good enough for designing logic CMOS gates based on their functionality . . .
- . . . it is not good enough for determining the performance in terms of switching speed and power dissipation

# Lecture outline

- First we are going to learn how to calculate the voltage dependence of the ON resistance (or rather the ON conductance) of the MOSFET based on the principles of the field-effect.
- Then we are going to learn why, for any gate voltage, there is a maximum current that a MOSFET switch can deliver or sink.

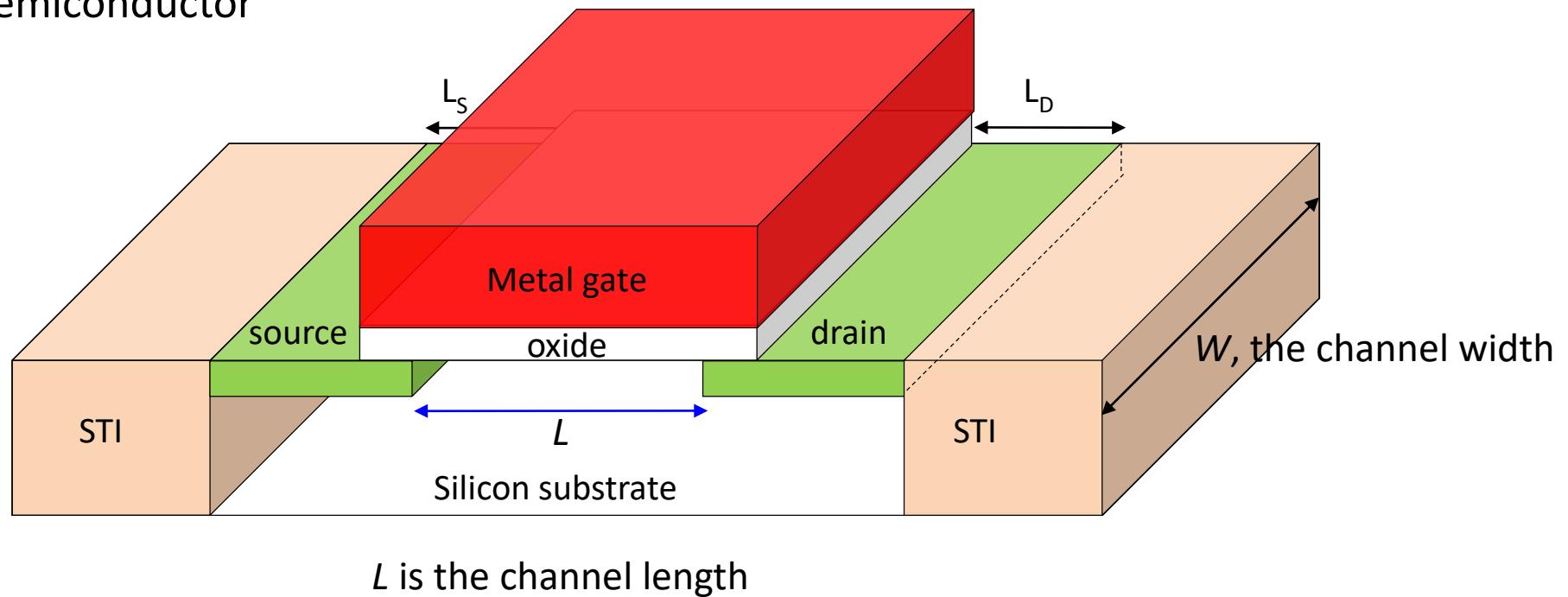
# MOSFET output and transfer characteristics



*The MOSFET is basically a “square-law” device!*

# The MOSFET structure

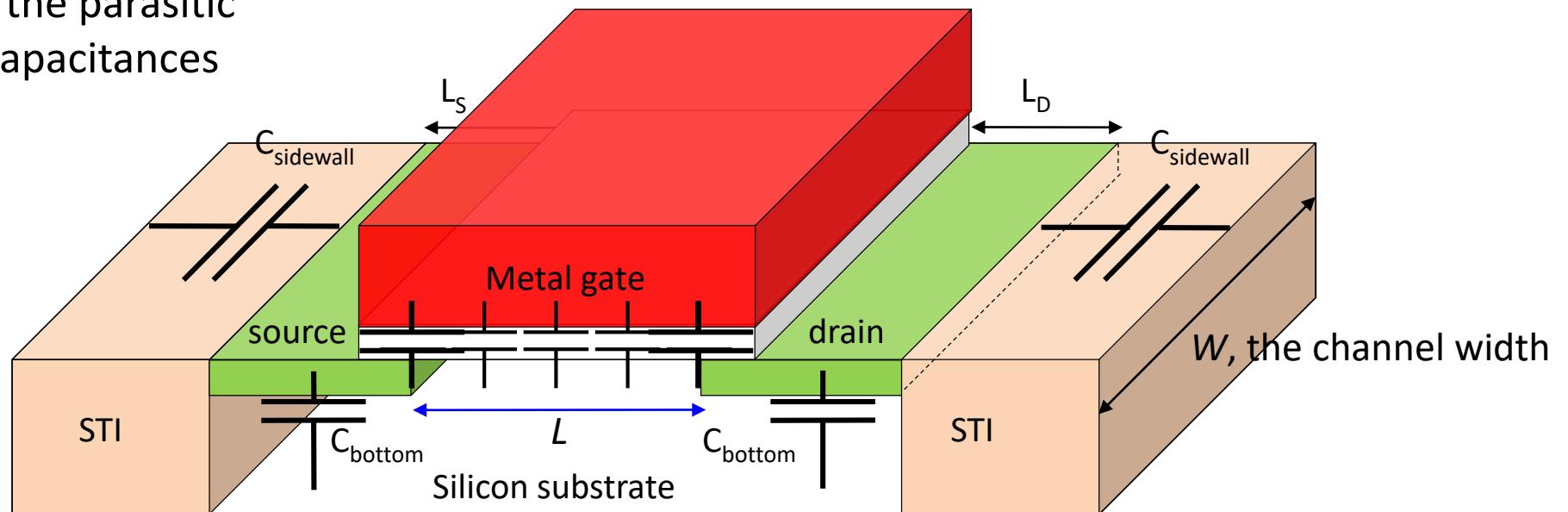
The metal-oxide-semiconductor structure



# The MOSFET capacitances

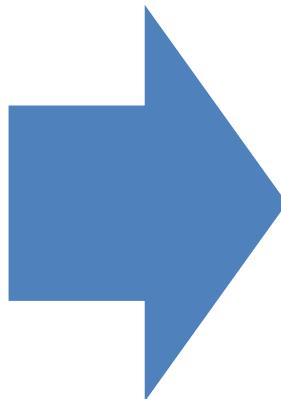
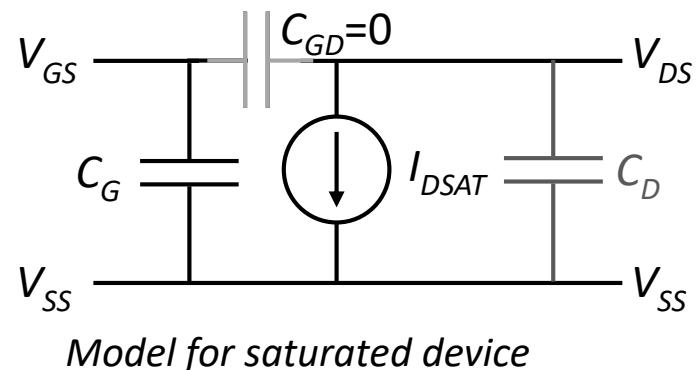
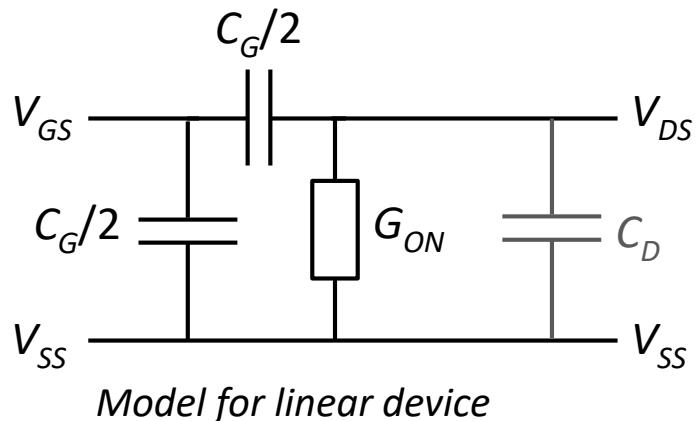
There is a distributed gate capacitance that must be lumped to the available ckt nodes, i.e. to source and drain

And then we have the parasitic source and drain capacitances

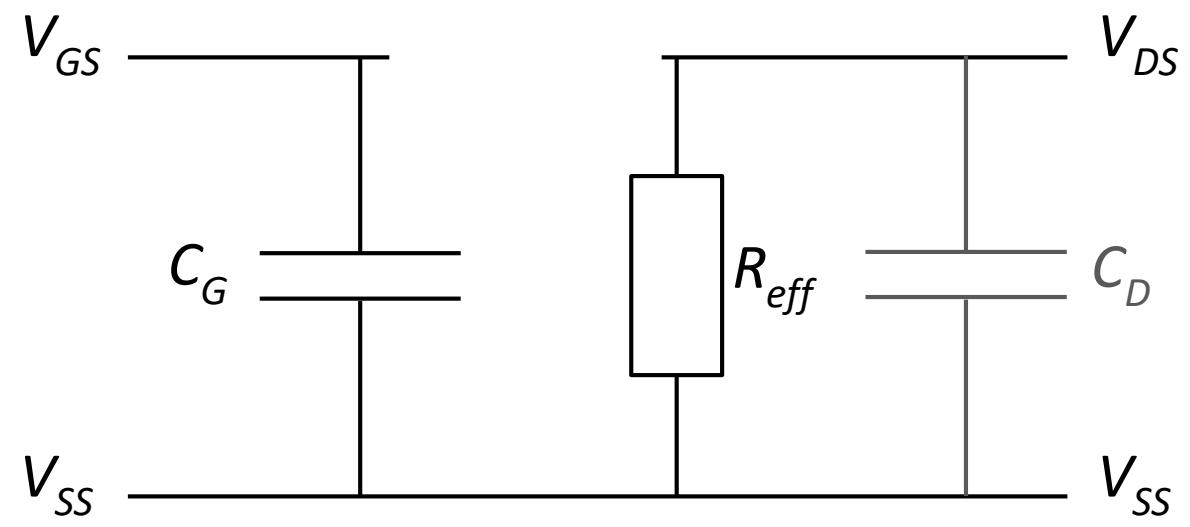


$L$  is the channel length

# Equivalent electrical two-port circuit model



The distributed gate to channel capacitance must be lumped to the available ckt nodes, i.e. to source and drain

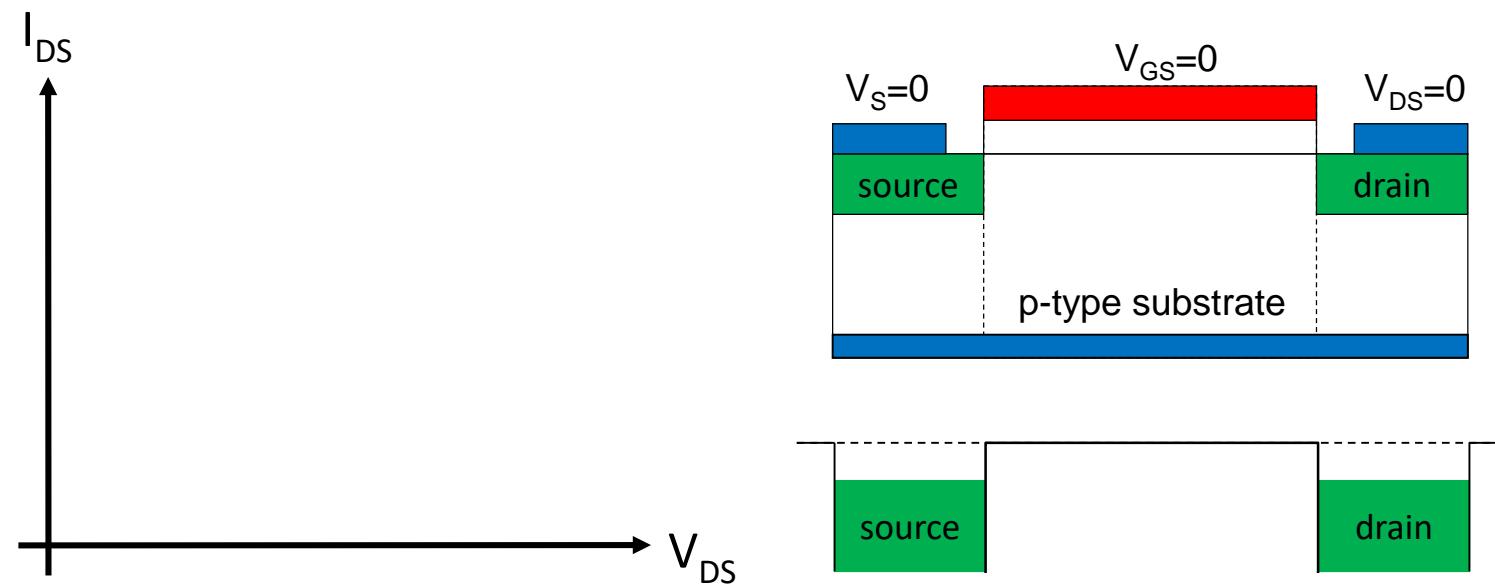
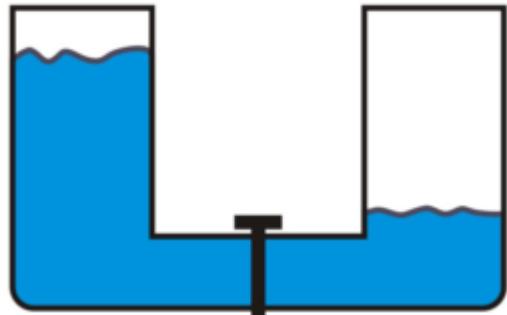


*“Average” model during switching of device output*

$C_G = WLC_{ox}$ , where  $C_{ox}$  is the gate insulator capacitance per unit area, typically  $20 \text{ fF}/\mu\text{m}^2$

$C_D = pC_G$ , where  $p$  is a certain fraction of the gate capacitance, typically  $p=1$

# ON/OFF MOSFET operation



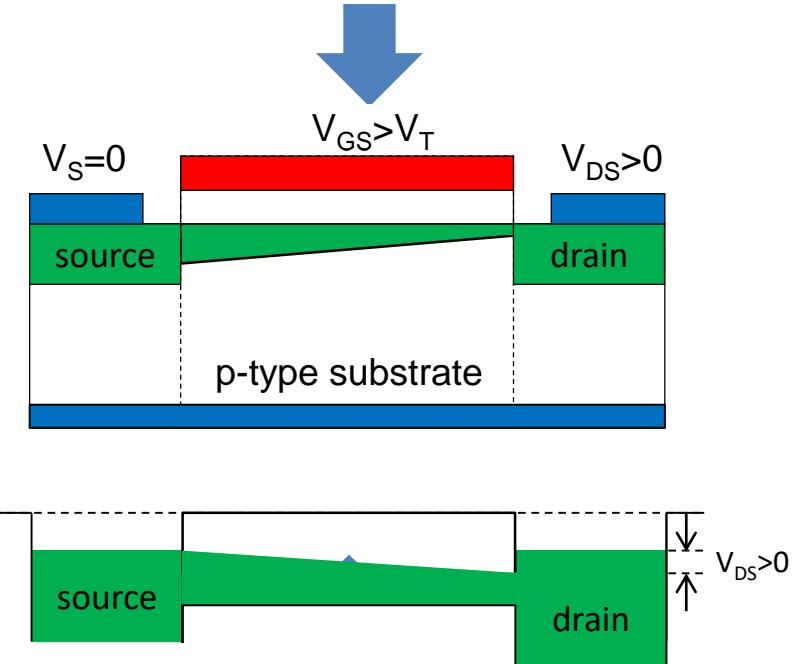
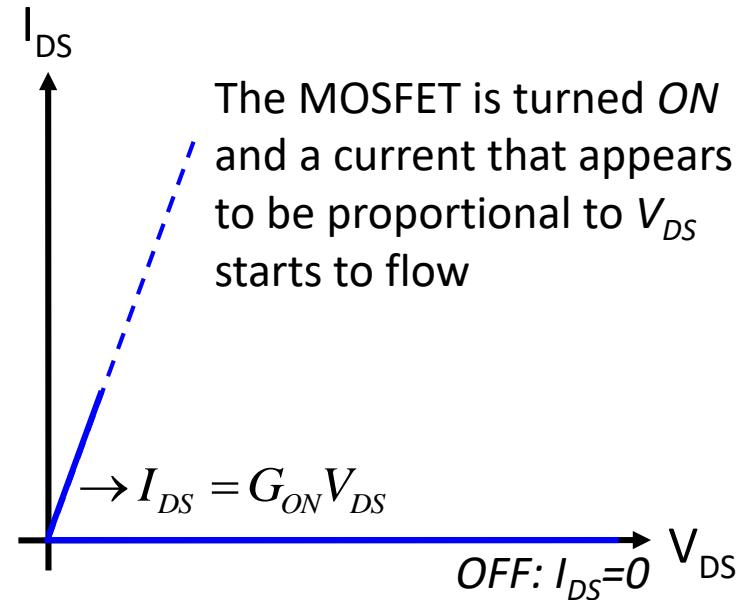
In this illustration of the MOSFET operation, the source and drain will be considered like two oceans of charge carriers isolated from each other through a potential barrier.

# ON/OFF MOSFET operation

What if we apply small drain voltage? – The drain level is lowered, but the source is still isolated by the potential barrier!

However, applying a certain gate voltage called the threshold voltage  $V_T$  will just about remove the barrier.

Increasing the gate voltage beyond the threshold voltage will lower the potential barrier at the source even further and form a conducting channel between source and drain.



In this illustration of the MOSFET operation, the source and drain will be considered like two oceans of charge carriers isolated from each other through a potential barrier.

# Calculating the ON conductance, $G_{ON}$

For calculating the ON conductance  $G_{ON}$ , let's have a look at the mobile charge in the channel!

Mobile charge  $Q_s$  at source (per unit length):

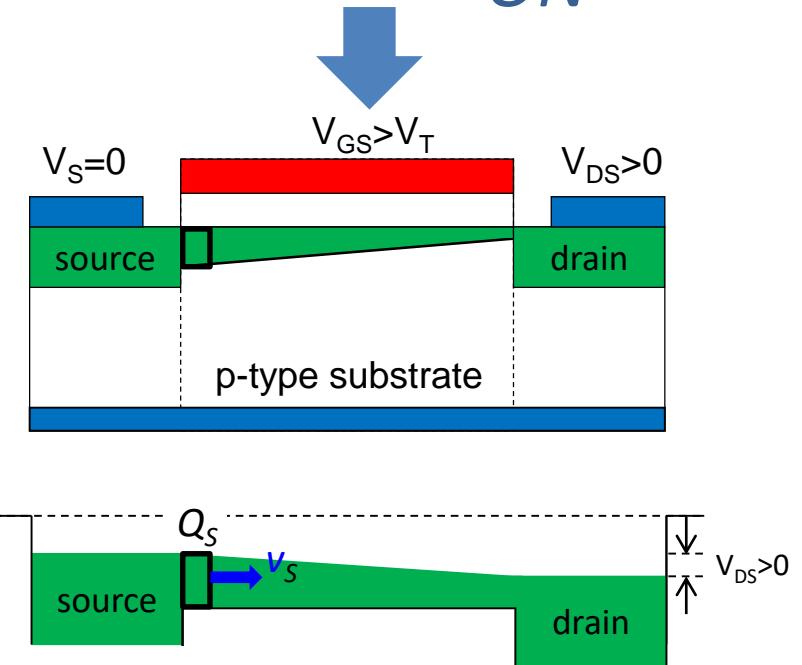
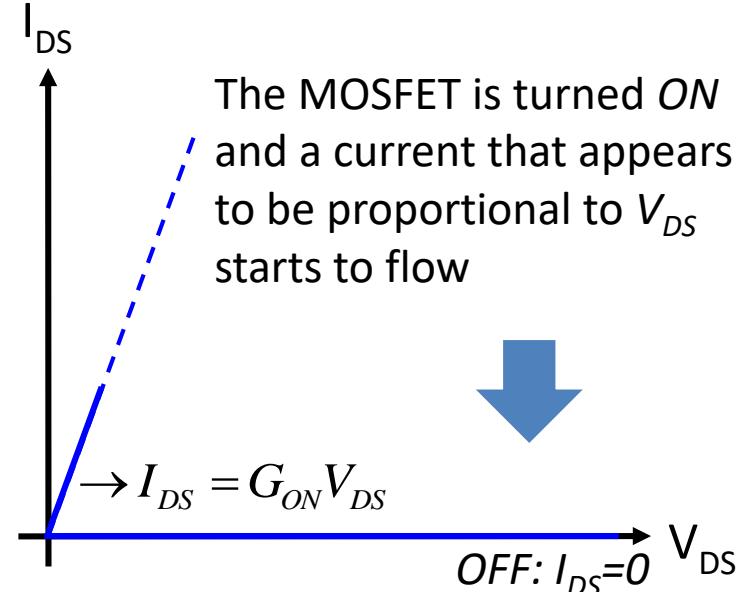
$$Q_s = WC_{ox} (V_{GS} - V_T) = WC_{ox} V_{GT}$$

Charge carrier drift velocity at the source:  $v_s = \mu E$ ,  $E = V_{DS}/L$

Drain current:  $I_{DS} = Q_s \times v_s$

If we introduce the conductance parameter  $k = \frac{W}{L} \mu C_{ox}$

The drain current can be written  $I_{DS} = k V_{GT} V_{DS}$



In this illustration of the MOSFET operation, the source and drain will be considered like two oceans of charge carriers isolated from each other through a potential barrier.

# Having a closer look along the channel

Mobile charge  $Q_S$  at source (per unit length):

$$Q_S = WC_{ox} (V_{GS} - V_T) = WC_{ox} V_{GT}$$

Mobile charge  $Q_D$  at drain (per unit length):

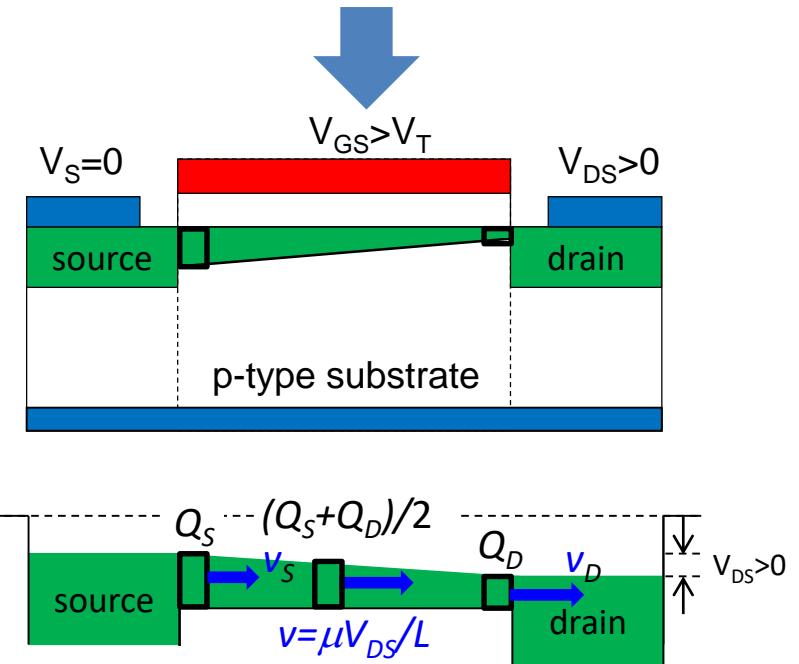
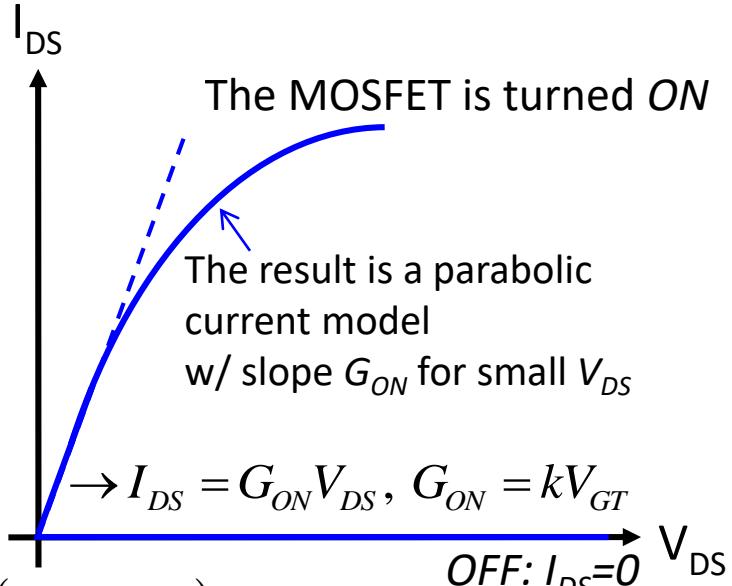
$$Q_D = WC_{ox} (V_{GS} - V_{DS} - V_T) = WC_{ox} (V_{GT} - V_{DS})$$

Here,  $Q_D < Q_S$  because of the drain voltage.

Hence, drift velocity is higher at drain than at source,  $v_D > v_S$ ,

This follows from the current being constant along the channel.

A thorough analysis based on the classical “gradual channel approximation” shows that the drain current is given by the average mobile charge density  $(Q_S + Q_D)/2$  times the average drift velocity  $v = \mu V_{DS}/L$



$C_{ox}$  is the gate capacitance per unit area  
 $W$  is the channel width

$V_{GT} = V_{GS} - V_T$  is the gate voltage overdrive

$\mu$  is the charge carrier mobility [ $\text{cm}^2/\text{Vs}$ ]

$E = V_{DS}/L$  is the electric field along the channel

# Understanding current saturation

The drain current seems to saturate as  $V_{DS} \rightarrow V_{GT}$

Mobile charge  $Q_S$  at source (per unit length):

$$Q_S = WC_{ox} (V_{GS} - V_T) = WC_{ox} V_{GT}$$

Mobile charge  $Q_D$  at drain (per unit length):

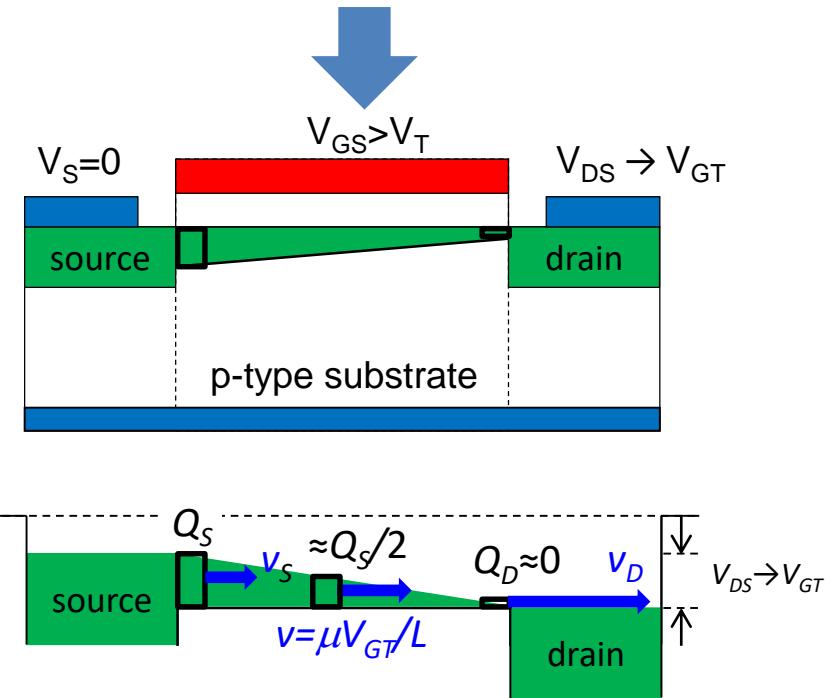
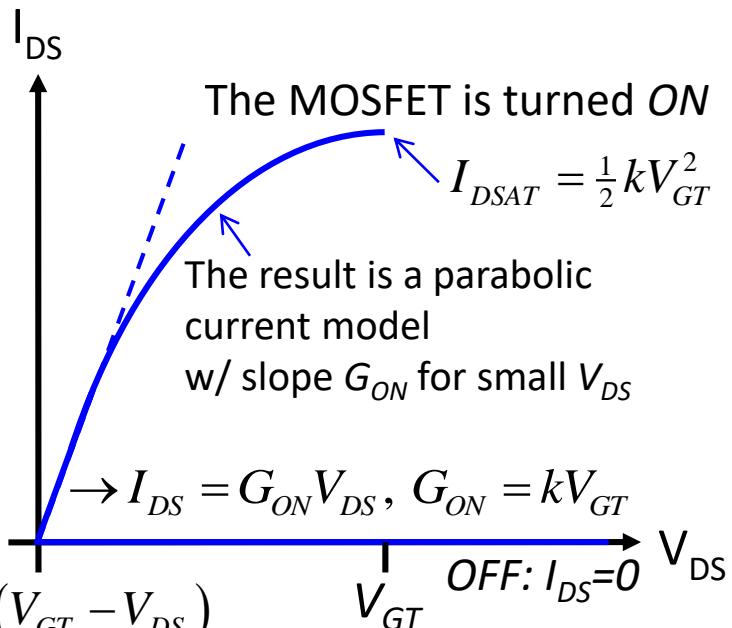
$$Q_D = WC_{ox} (V_{GS} - V_{DS} - V_T) = WC_{ox} (V_{GT} - V_{DS})$$

Here,  $Q_D \rightarrow 0$  when  $V_{DS} \rightarrow V_{GT}$

Hence, drift velocity at drain approaches “infinity”, i.e.  $v_D \rightarrow \infty$ .

This follows from the current being constant along the channel.

Hence, the drain current  $I_{DS} \rightarrow$  charge  $Q_S/2 \times$  drift velocity  $\mu V_{GT}/L$  as  $V_{DS} \rightarrow V_{GT}$

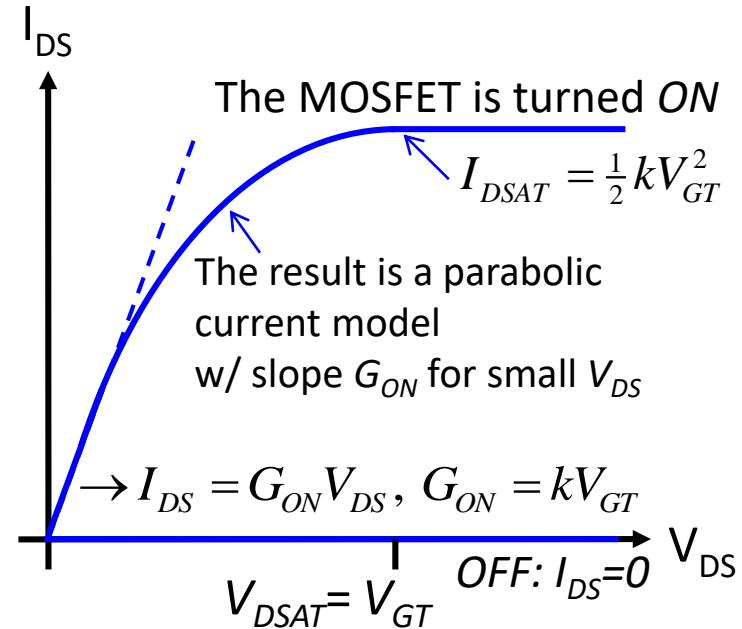


$C_{ox}$  is the gate capacitance per unit area  
 $W$  is the channel width  
 $V_{GT} = V_{GS} - V_T$  is the gate voltage overdrive  
 $\mu$  is the charge carrier mobility [ $\text{cm}^2/\text{Vs}$ ]  
 $E = V_{DS}/L$  is the electric field along the channel

# Understanding current saturation

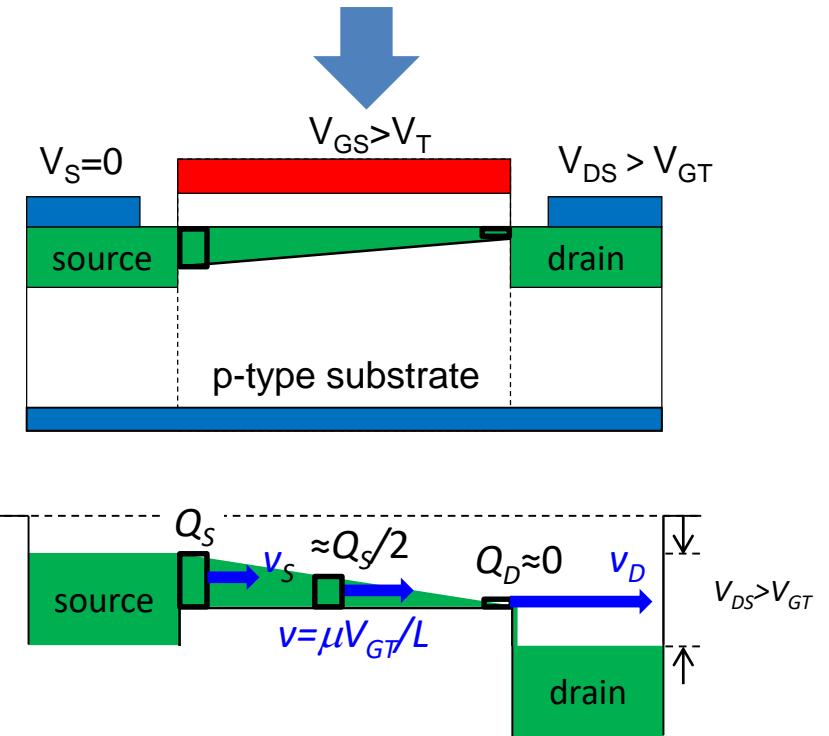
What if we increase the drain voltage beyond the gate voltage overdrive, i.e.  $V_{DS} > V_{GT}$

Actually, the conditions within the channel does not change with the height of the “water fall” between the drain end of the channel and the drain!



Drain current stays constant!

The saturation current  $I_{DSAT}$  is given by the gate voltage overdrive  $V_{GT}$  squared!



The saturation voltage  $V_{DSAT}$  is given by  $Q_D=0, \rightarrow V_{DSAT}=V_{GS}-V_T$ , i.e. the gate voltage overdrive  $V_{GT}$

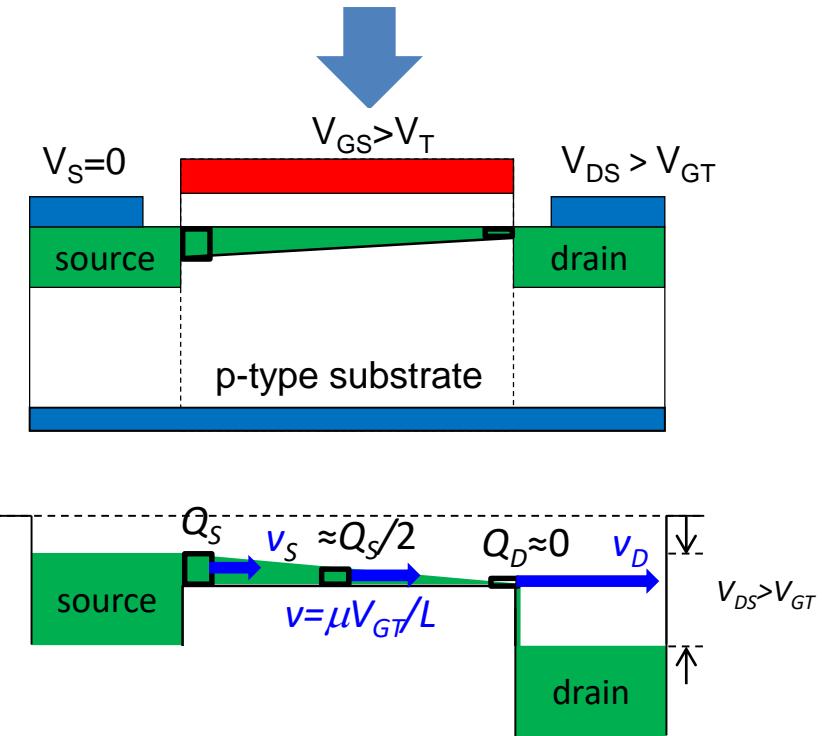
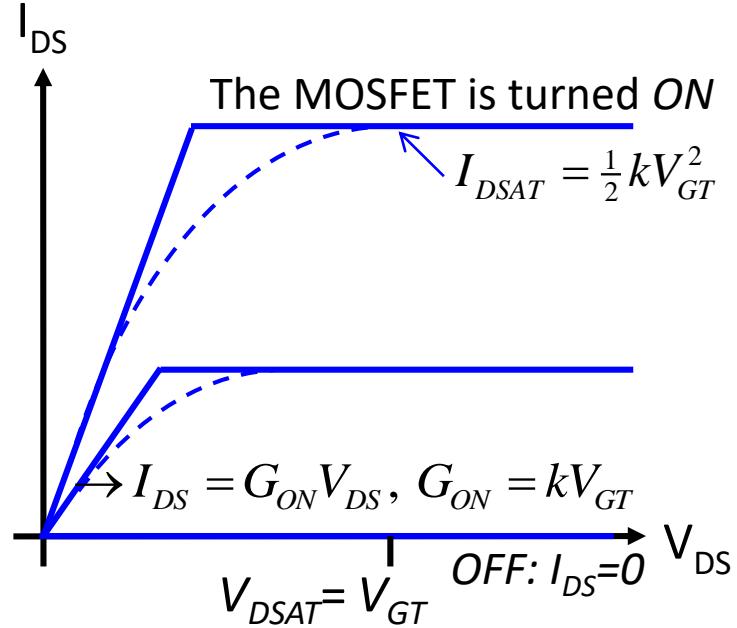
# Piecewise linear MOSFET Model

What if we simplify the model, focusing on the two main behaviors of the MOSFET?

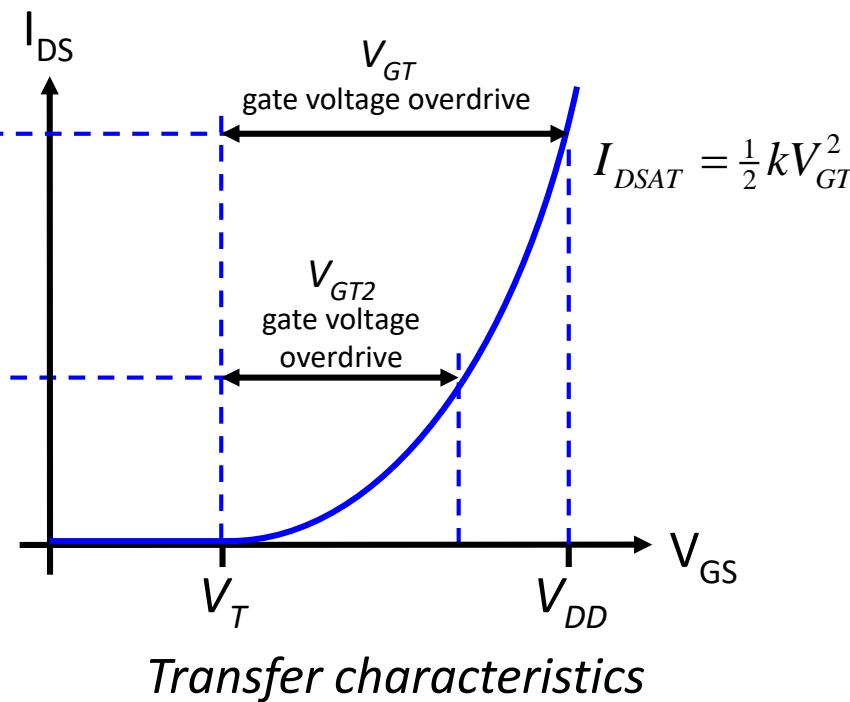
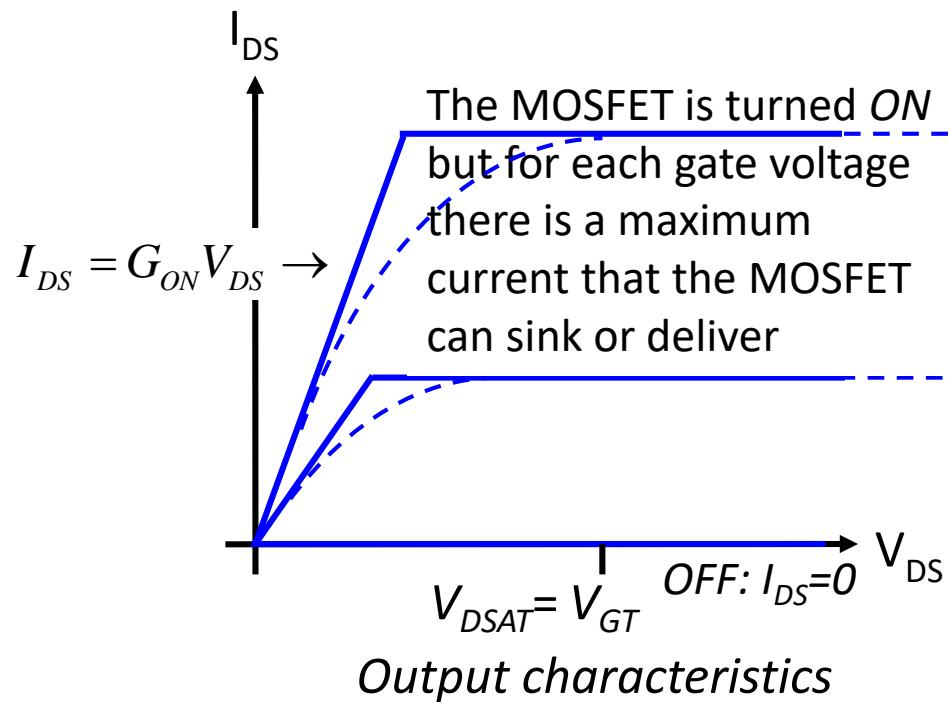
Linear behavior for small drain voltages -  $G_{ON}$

Saturated behavior for large drain voltages -  $I_{DSAT}$

What if we decrease the gate voltage overdrive?



# MOSFET output and transfer characteristics



*The MOSFET is basically a “square-law” device!*

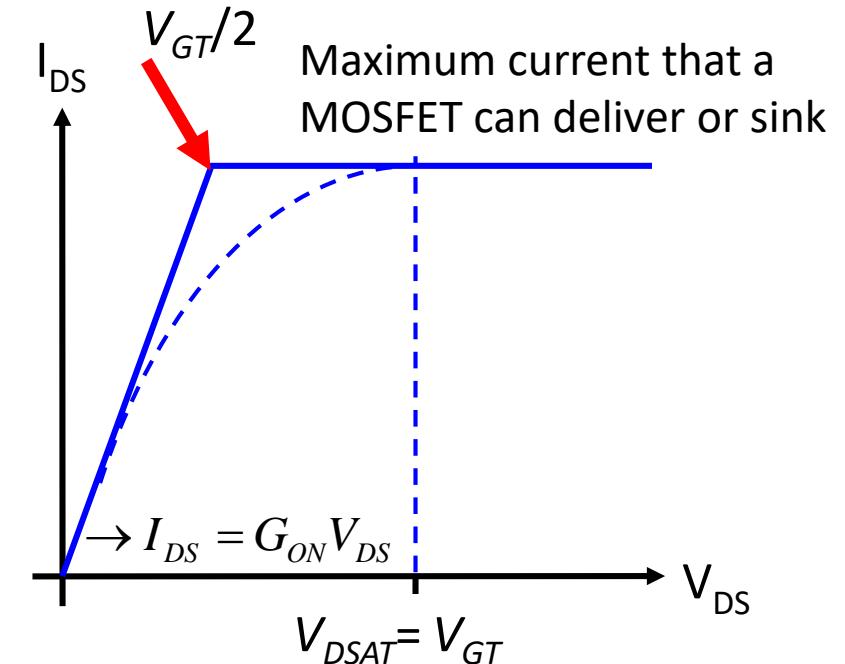
# Example

A fully turned on MOSFET has an on resistance of  $1 \text{ k}\Omega$ . What is the maximum current that this device can deliver or sink? Assume  $V_{DD} = 1.2 \text{ V}$ , and  $V_T = 0.3 \text{ V}$ .

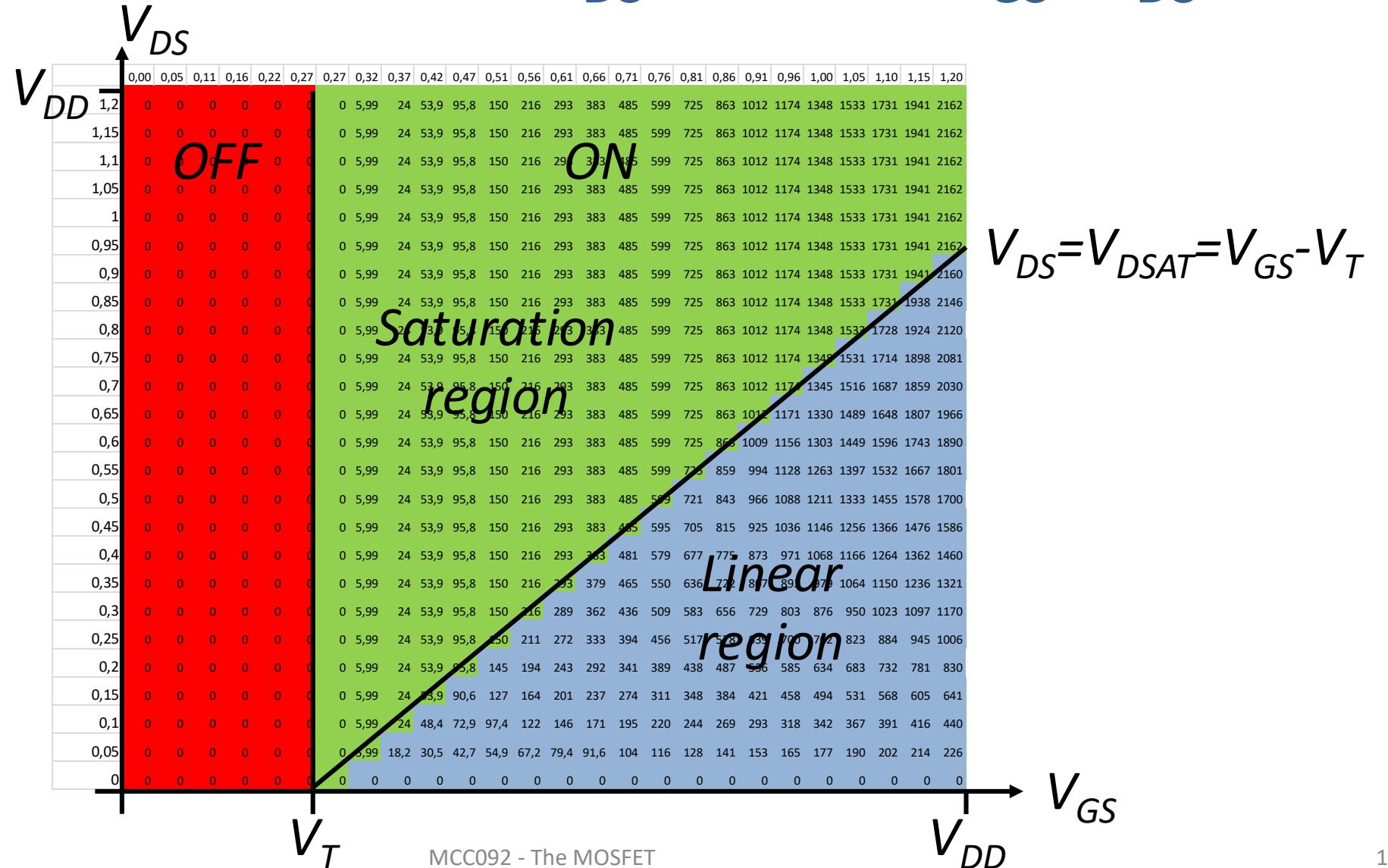
**Solution:** We know that a long-channel MOSFET saturates for  $V_{DSAT} = V_{GT} = V_{GS} - V_T$ . Hence, in this case we have  $V_{DSAT} = 0.9 \text{ V}$ .

Since the MOSFET is a square-law device (w/ parabolic I-V model) we know that the piecewise linear model breakpoint occurs at  $V_{GT}/2$ .

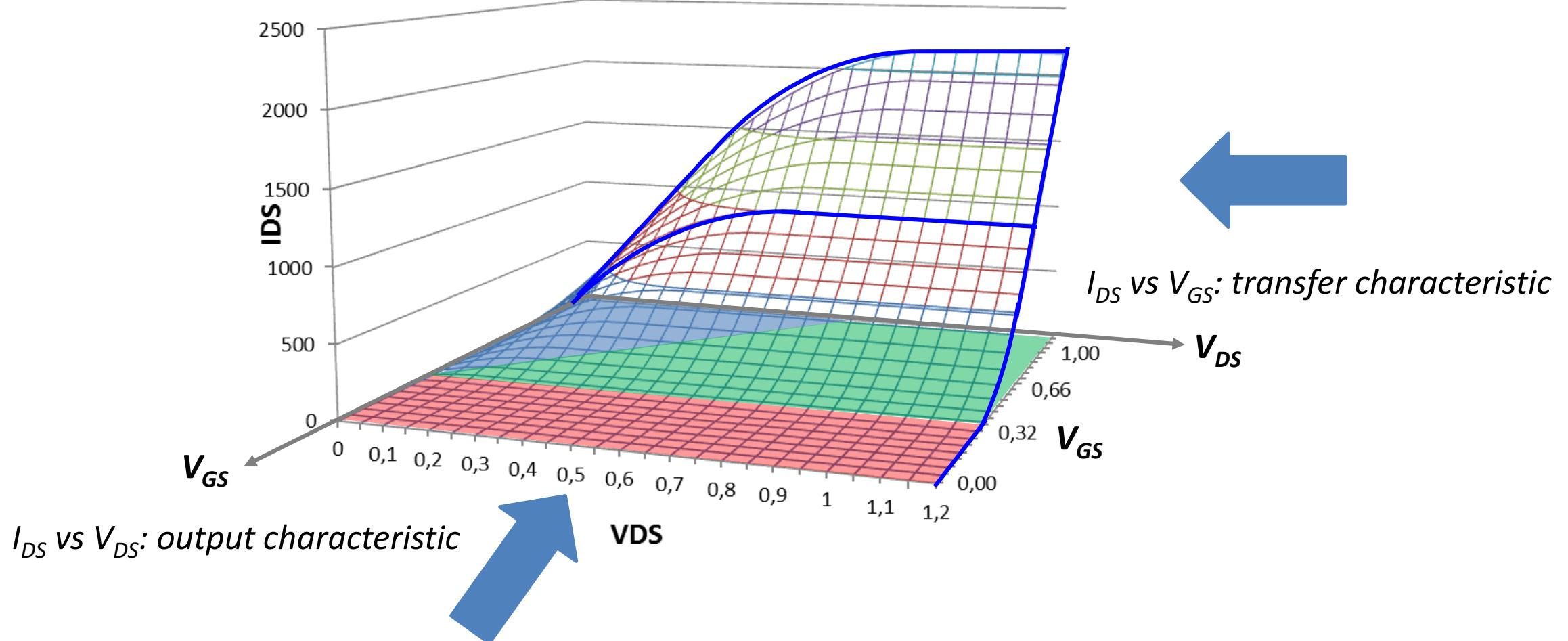
Hence, maximum current is given by  $I_{DS} = G_{ON}V_{DS} = \frac{V_{GT}/2}{R_{ON}} = \frac{0.45}{1} = 450 \mu\text{A}$



# Model can predict $I_{DS}$ for any $V_{GS}/V_{DS}$



$I_{DS}$  can be plotted in 3D vs.  $V_{GS}$  &  $V_{DS}$



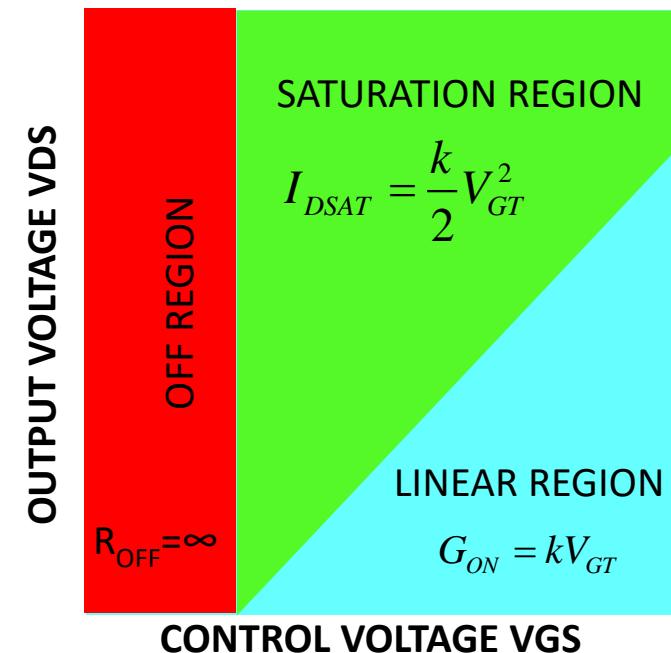
# MOSFET regions of operation

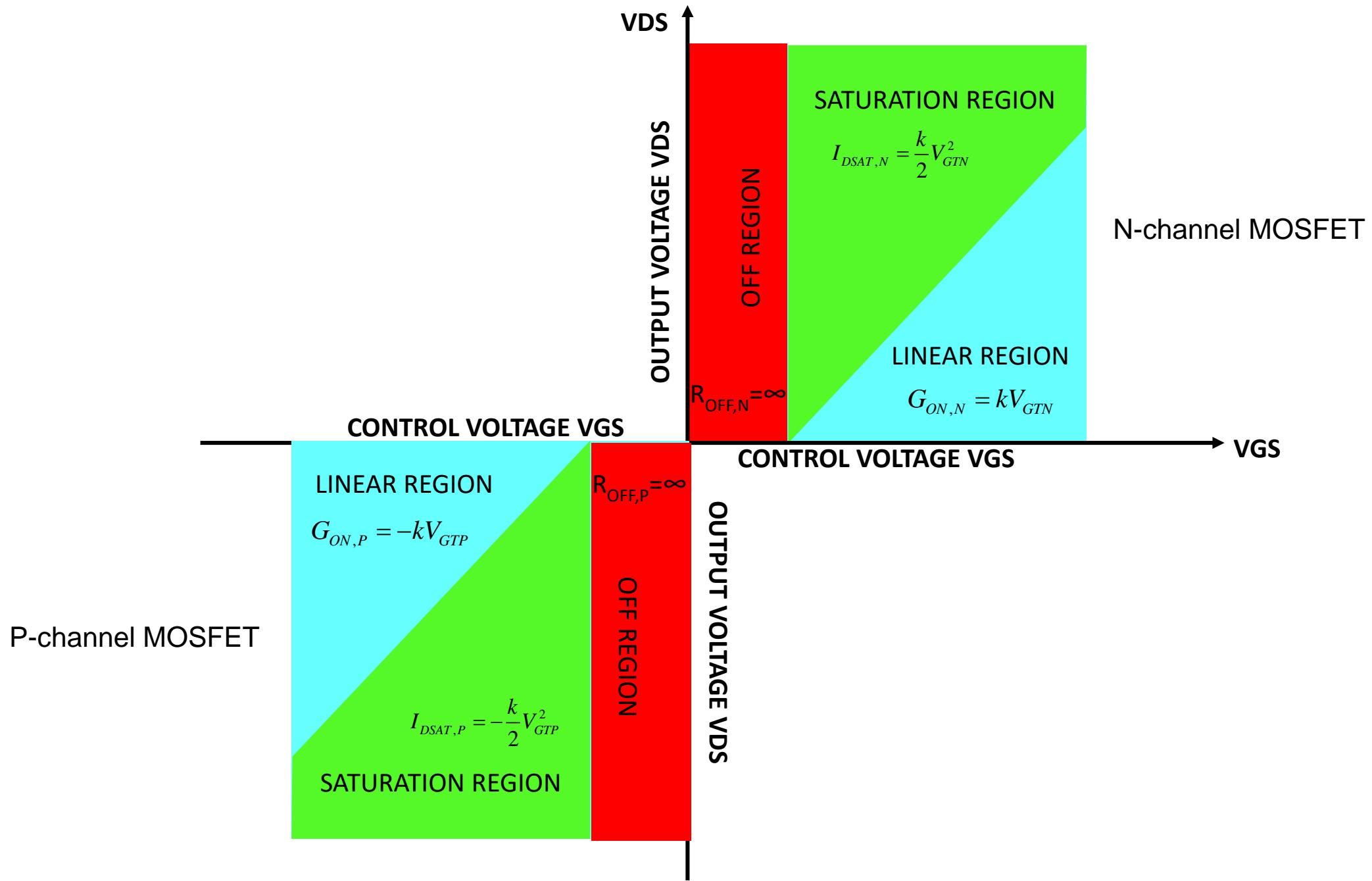
- Why are colored MOSFET regions of operation important?
- Because they visualize the formula to use for estimating the drain current

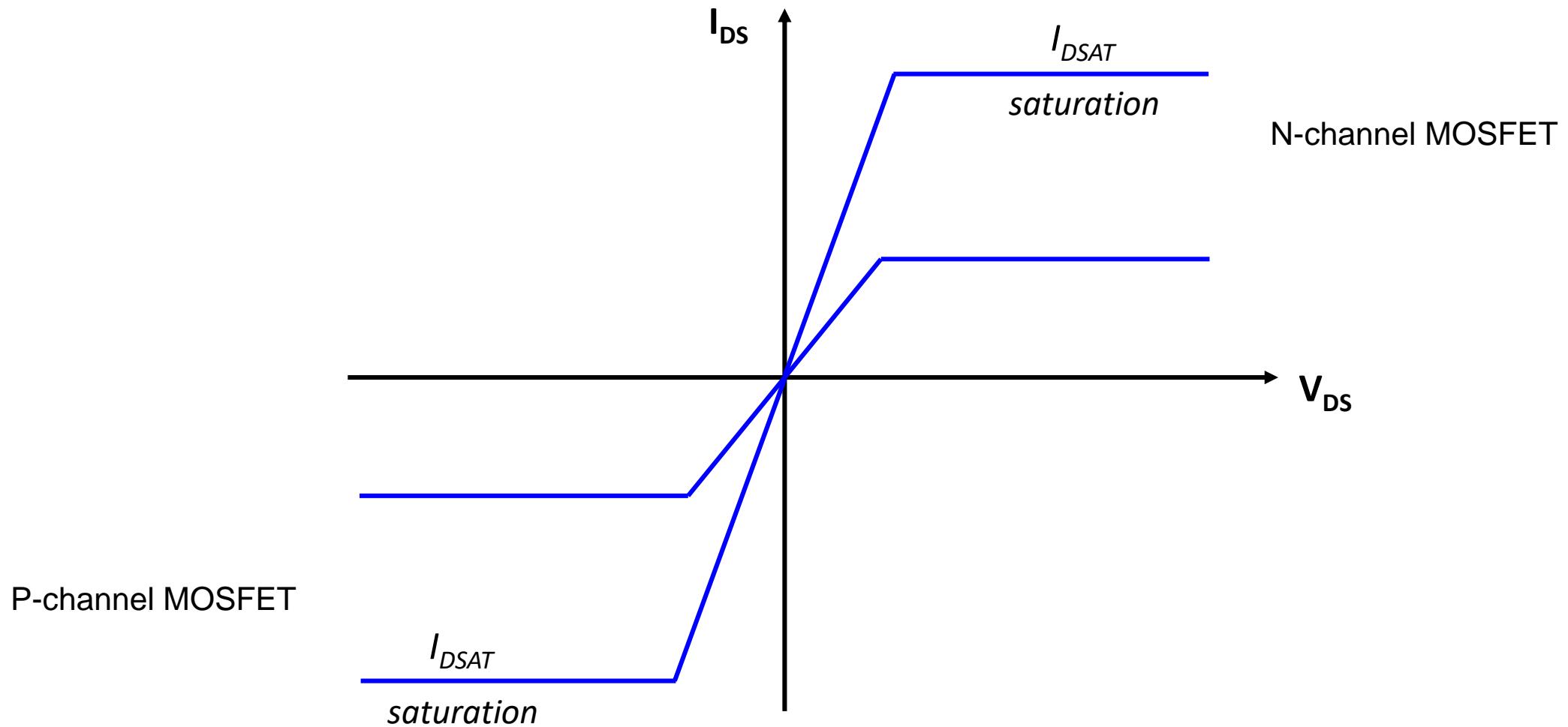
$$I_{DSUB} = 0$$

$$I_{DS} = k \left( V_{GT} - \frac{V_{DS}}{2} \right) V_{DS} = G_{ON} V_{DS} \left( 1 - \frac{V_{DS}}{2V_{GT}} \right)$$

$$I_{DSAT} = \frac{k}{2} V_{GT}^2$$



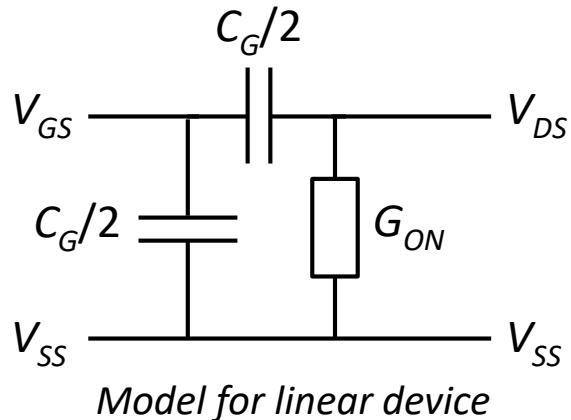




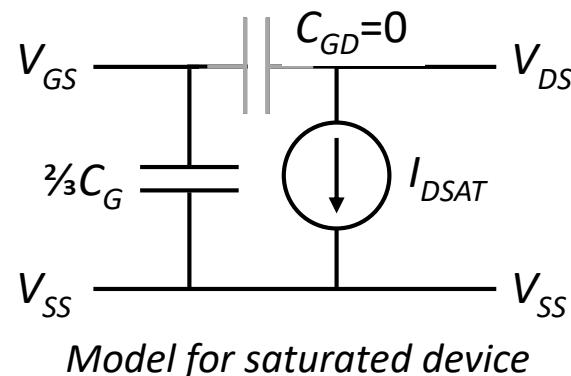
# Summary

- In this lecture, The MOSFET has been regarded as an electrically controlled ON/OFF switch.
- Input and output voltages are referred to source
  - Current controlling gate voltage  $V_{GS}$ .
  - The output drain voltage  $V_{DS}$ .
- The MOSFET current is a function of both voltages,  $V_{GS}$  and  $V_{DS}$ .
- When ON, the MOSFET behaves
  - like a resistor  $R_{ON}$  in its linear region,
  - like a constant-current source  $I_{DSAT}$  in its saturation region.
- First-order approximation yields a square-law model for  $I_{DSAT}=f(V_{GT}^2)$
- When OFF, there is a subthreshold leakage current,  $I_{SUB}$ .
- Very useful to color code the three regions of operation
  - Red for OFF
  - Green for ON and saturated (and blue for ON and linear operation)

# Equivalent electrical two-port circuit model



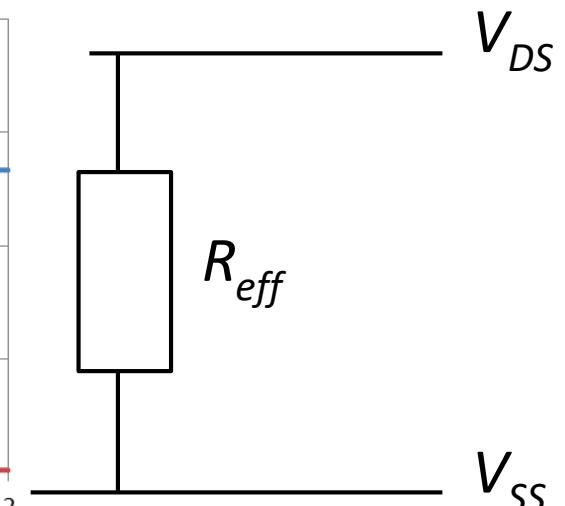
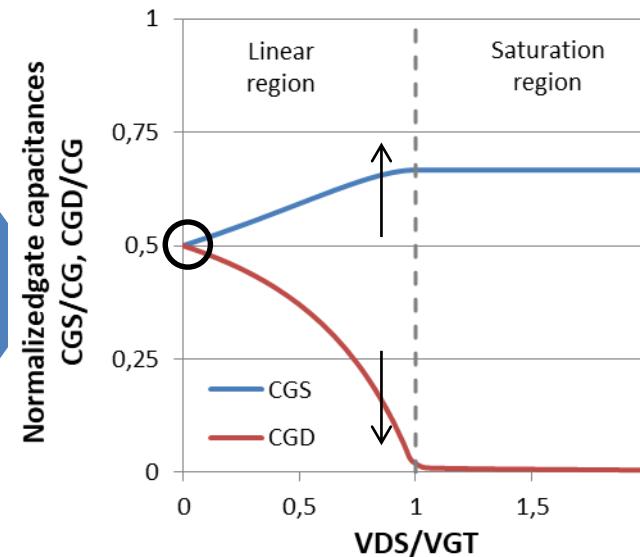
In the linear region, the capacitance splits equally between source and drain



In the saturation region, the capacitance tilts towards the source!

The field-effect upon which the operation of a MOSFET relies, gives the MOSFET a capacitive input!

The distributed gate to channel capacitance must be lumped to the available ckt nodes, i.e. to source and drain

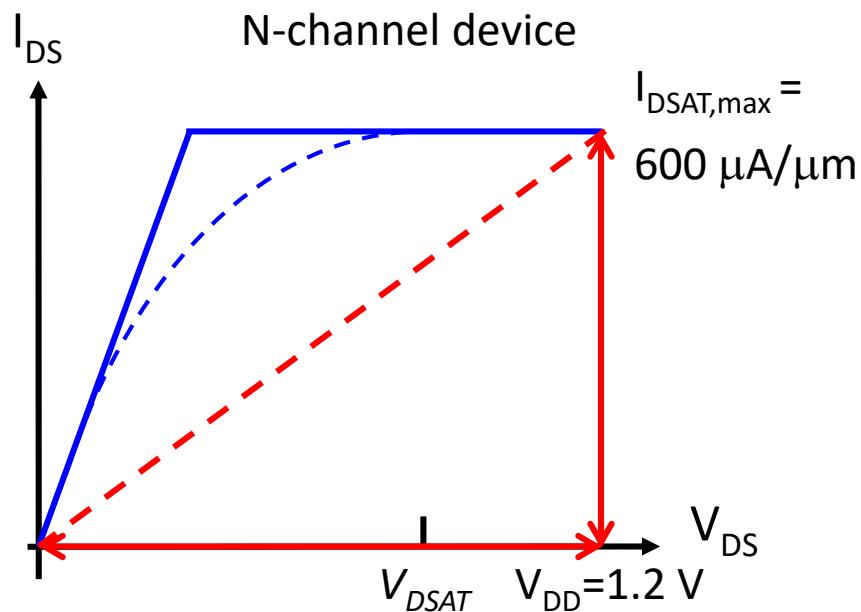


Q: Why use  $C_{GS}=C_G$  and not  $C_{GS}=2/3 C_G$ ?

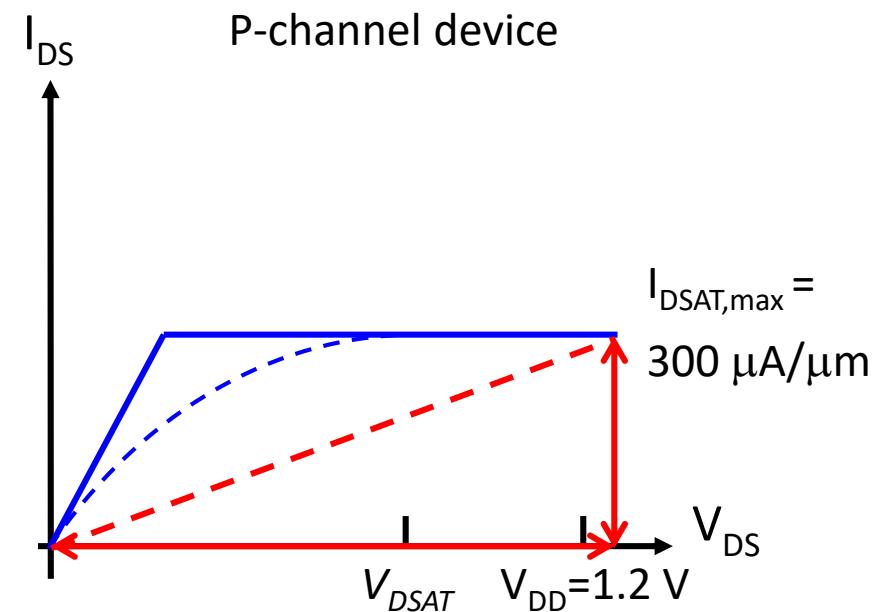
A: Integers are easier to handle and there are parasitic overlap and fringing field caps there to motivate the approximation!

# Effective resistances: 65 nm MOSFETs

$$R_{N,eff} = 2 \text{ k}\Omega \cdot \mu\text{m}$$



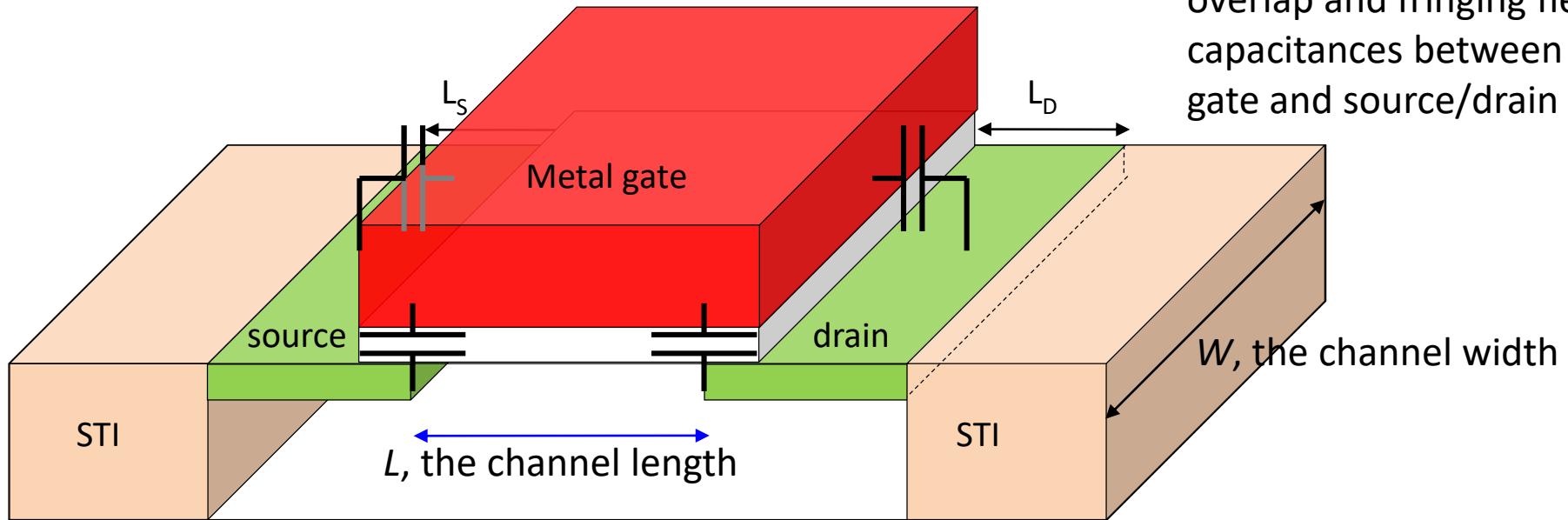
$$R_{P,eff} = 4 \text{ k}\Omega \cdot \mu\text{m}$$



Q: Why is there a difference between n- and p-channel effective resistances?

A: Hole mobility in p-channel device is only half of electron mobility in n-channel device!

# MOSFET gate capacitance



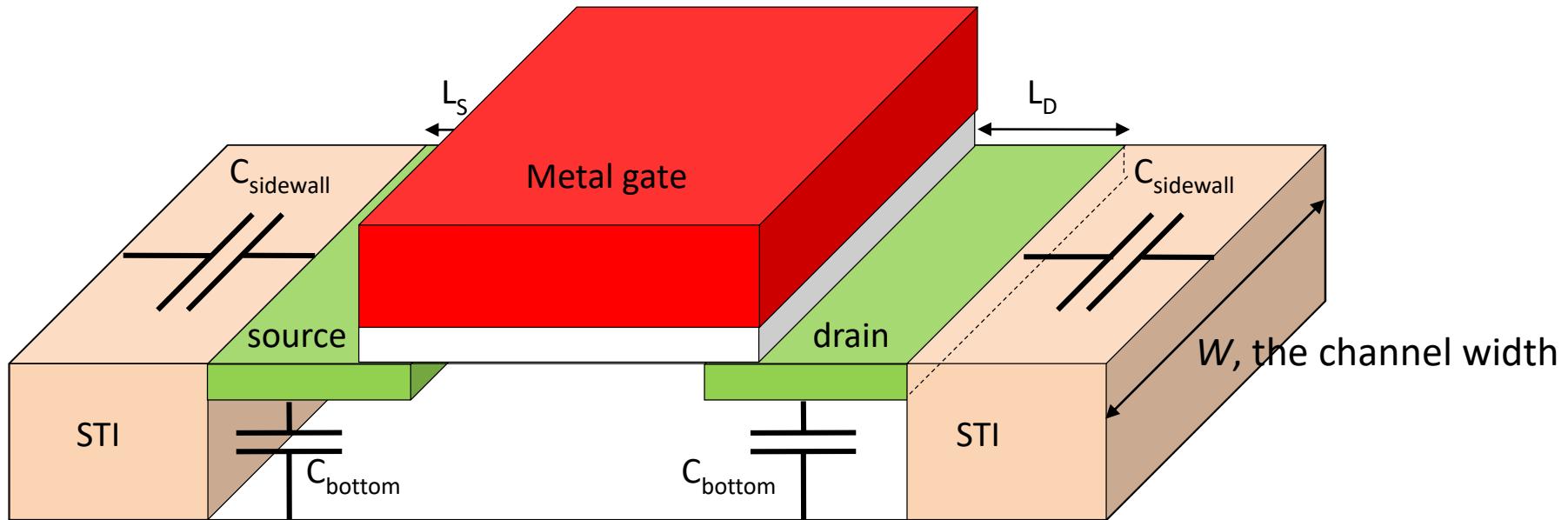
FYI, there are also parasitic overlap and fringing field capacitances between the gate and source/drain

The capacitance between gate and channel,  $C_G = WLC_{ox}$ , is intrinsic to the field effect!

In a 65 nm CMOS process, typically  $C_{ox} = 20 \text{ fF}/\mu\text{m}^2$

When using fixed channel lengths,  $L=65 \text{ nm}$ , as in digital designs, gate cap  $C_G$  scales with channel width

# Source/drain parasitic capacitances



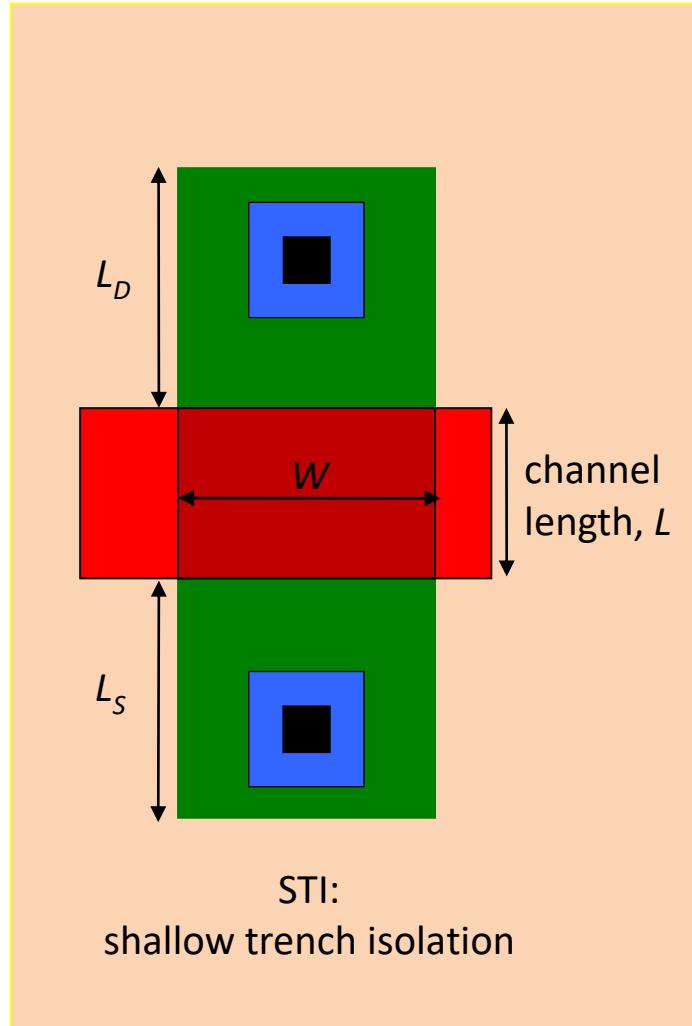
The source and drain capacitances are extrinsic to the field effect!

Therefore regarded as parasitic capacitances, but are non-negligible, i.e.  $C_D = pC_G$ , where  $p \approx 1$ .

Sidewall caps due to source/drain lateral dimensions  $L_S$  and  $L_D$ , are usually small

→ Just as for the gate cap, we will consider source/drain caps scalable with channel width

# 65 nm CMOS capacitances



$$C_{ox} \approx 20 \text{ fF}/\mu\text{m}^2$$

(corresponds to 1.2 nm effective oxide thickness)

60 nm effective channel length yields:  $C_G = 1.2 \text{ fF}/\mu\text{m}$

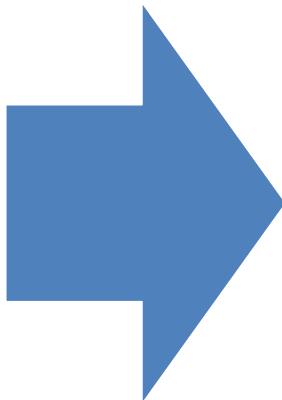
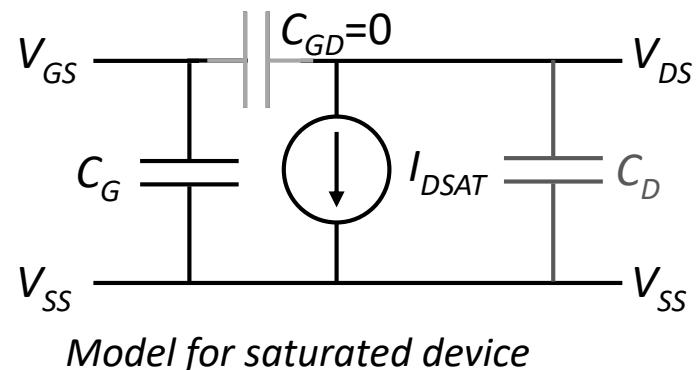
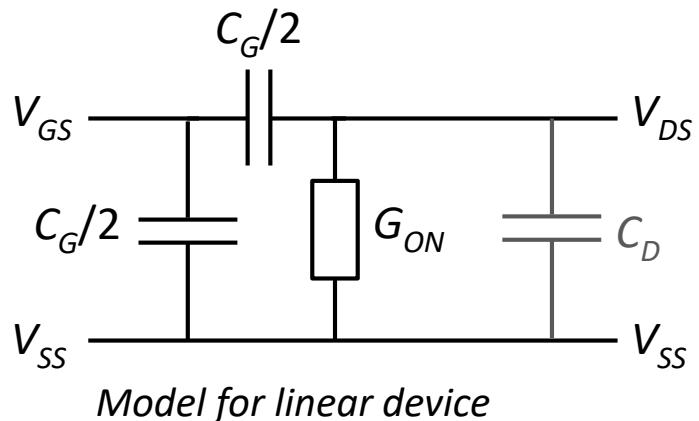
Drain/source parasitic caps

The parasitic caps are of the same order of magnitude as the gate capacitance,  $C_S = C_D = p C_G$

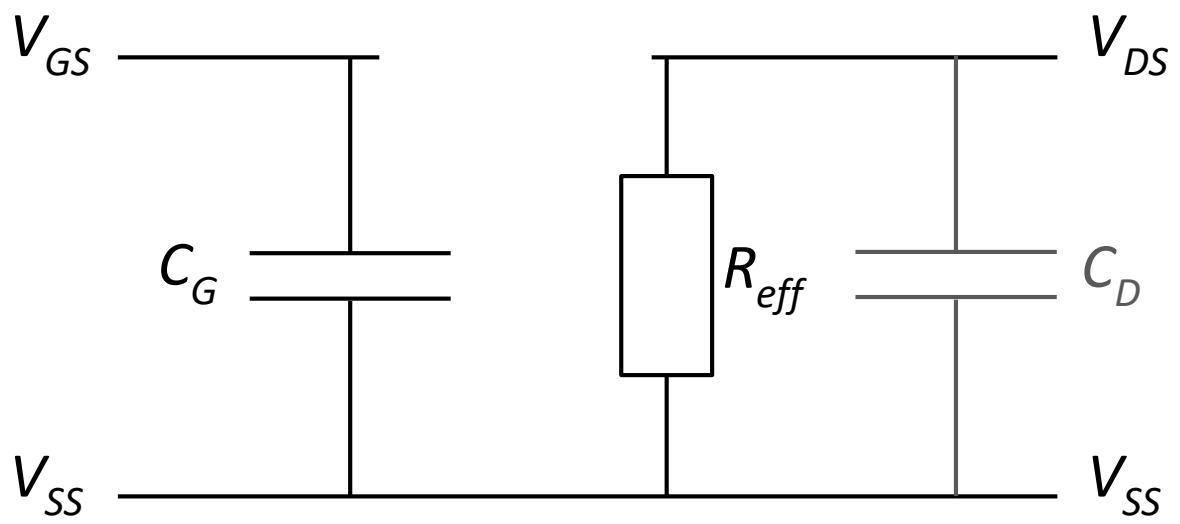
Generic approach is to use  $p=1$  for simplicity

But sometimes  $p=0.5$  or  $p=0.8$ !

# Equivalent electrical two-port circuit model



The distributed gate to channel capacitance must be lumped to the available ckt nodes, i.e. source and drain



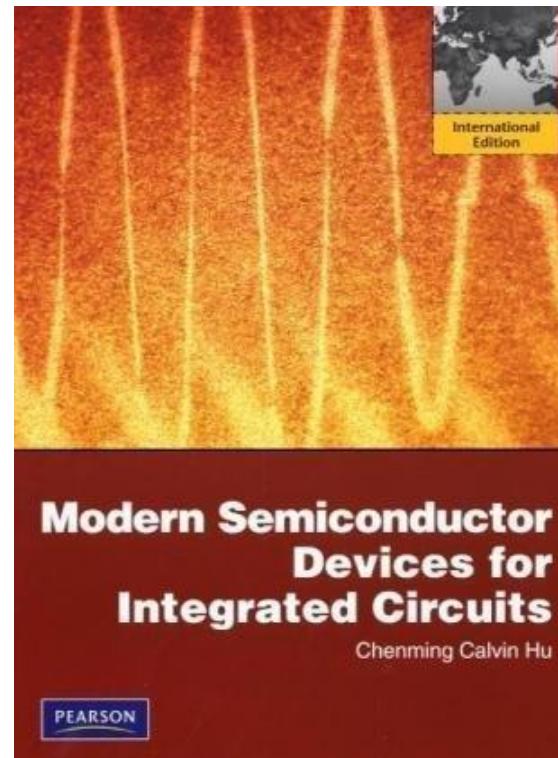
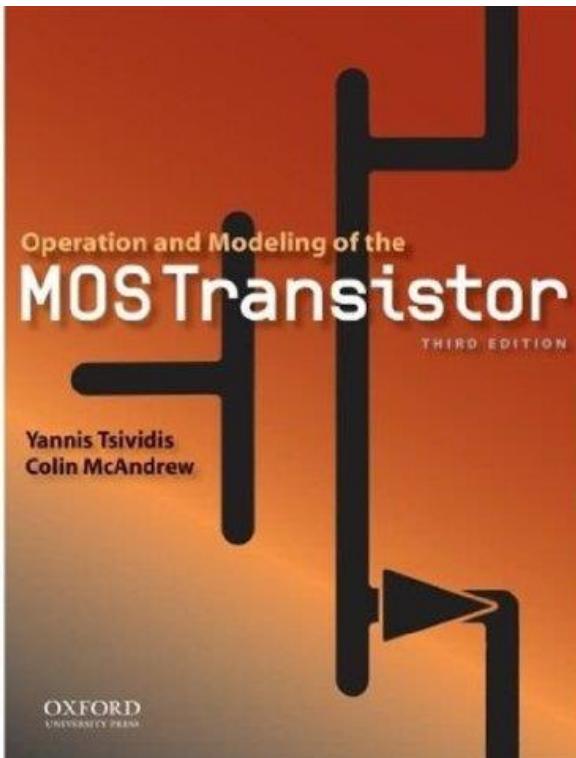
“Average” model during switching of device output

$C_G = WLC_{ox}$ , where  $C_{ox}$  is the gate insulator capacitance per unit area, typically  $20 \text{ fF}/\mu\text{m}^2$

$C_D = pC_G$ , where  $p$  is a certain fraction of the gate capacitance, typically  $p=1$

# The MOSFET in detail

- A number of textbooks treat MOSFET models in great detail, including their physical background and shortcomings due to short-channel effects in nanoscale devices



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## BSIM4v4.7 MOSFET Model

### -User's Manual

Tanvir Hasan Morshed, Darsen D. Lu, Wenwei (Morgan) Yang, Mohan V. Dunga, Xuelei (Jane) Xi, Jin He,  
Weidong Liu, Kanyu, M. Cao, Xiaodong Jin, Jeff J. Ou, Mansun Chan,  
Ali M. Niknejad, Chenming Hu

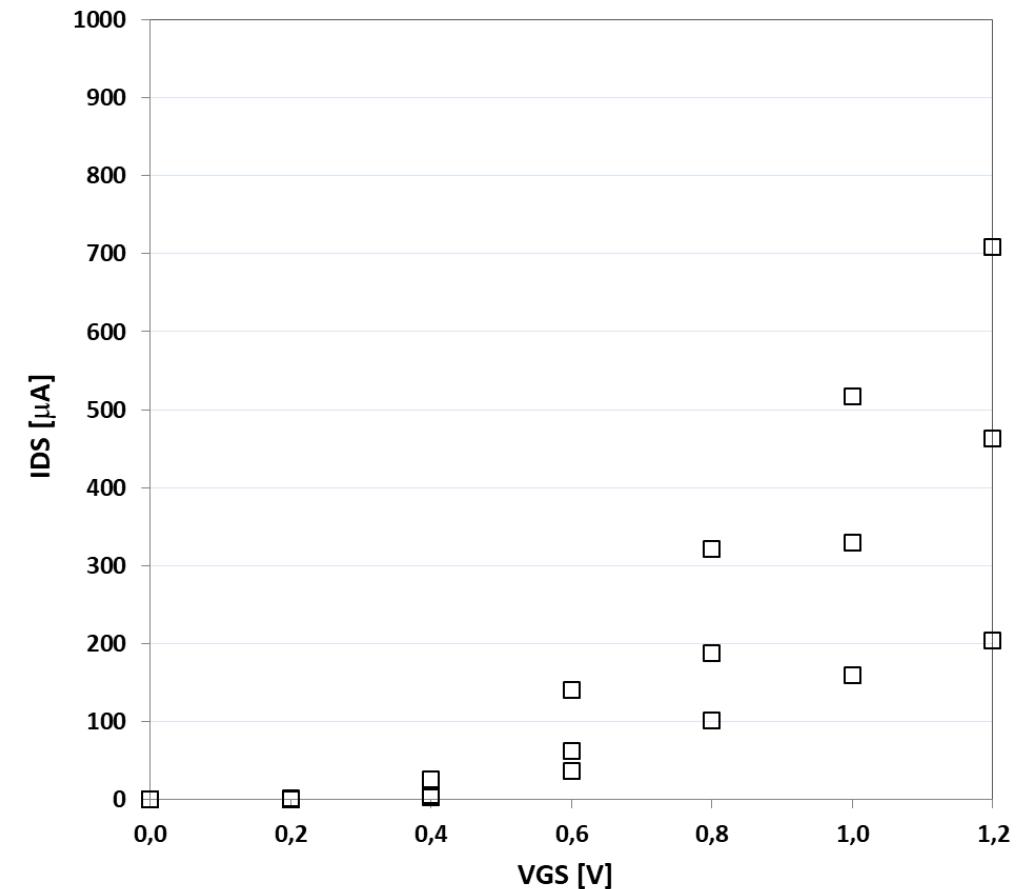
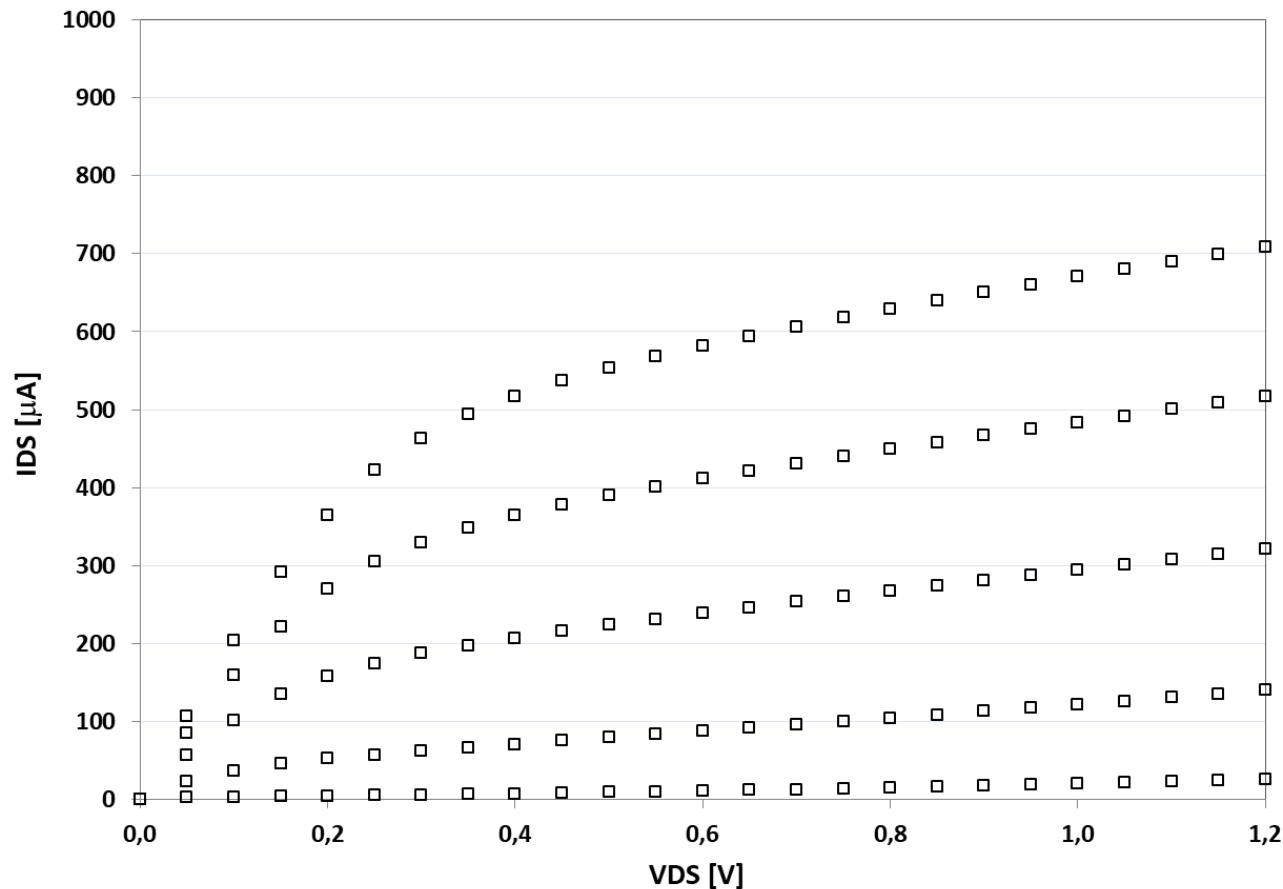
Department of Electrical Engineering and Computer Sciences  
University of California, Berkeley, CA 94720

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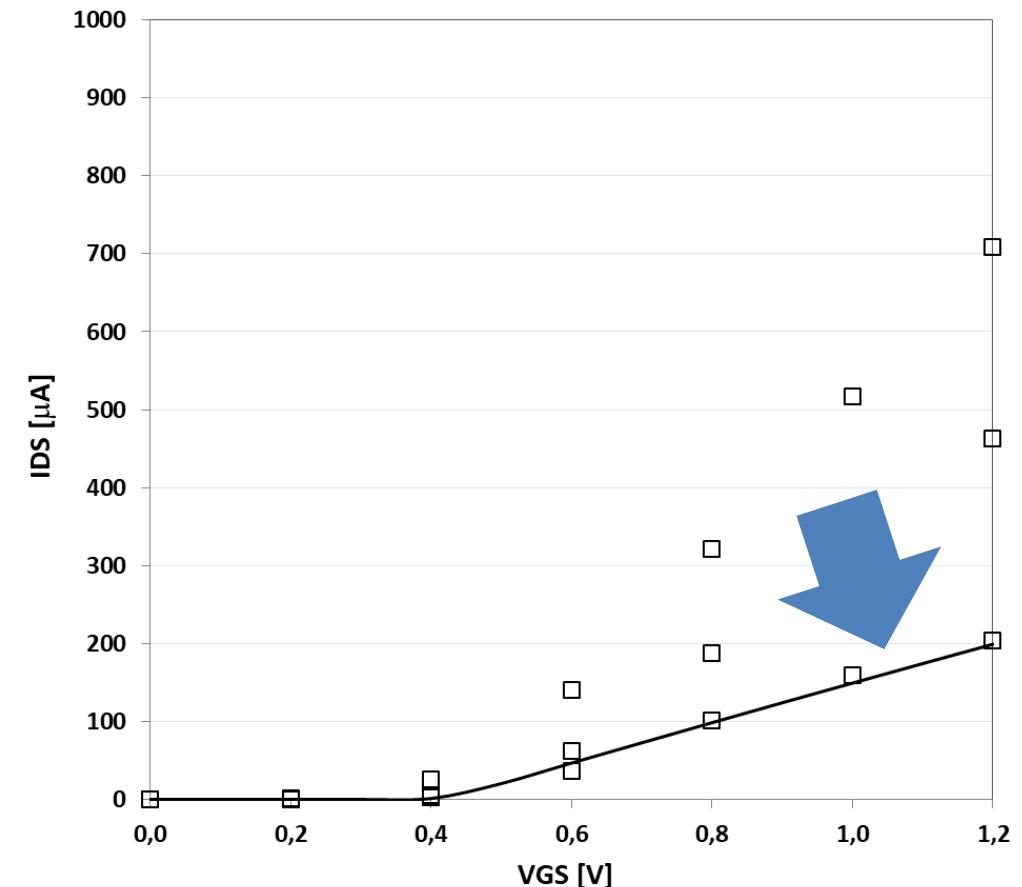
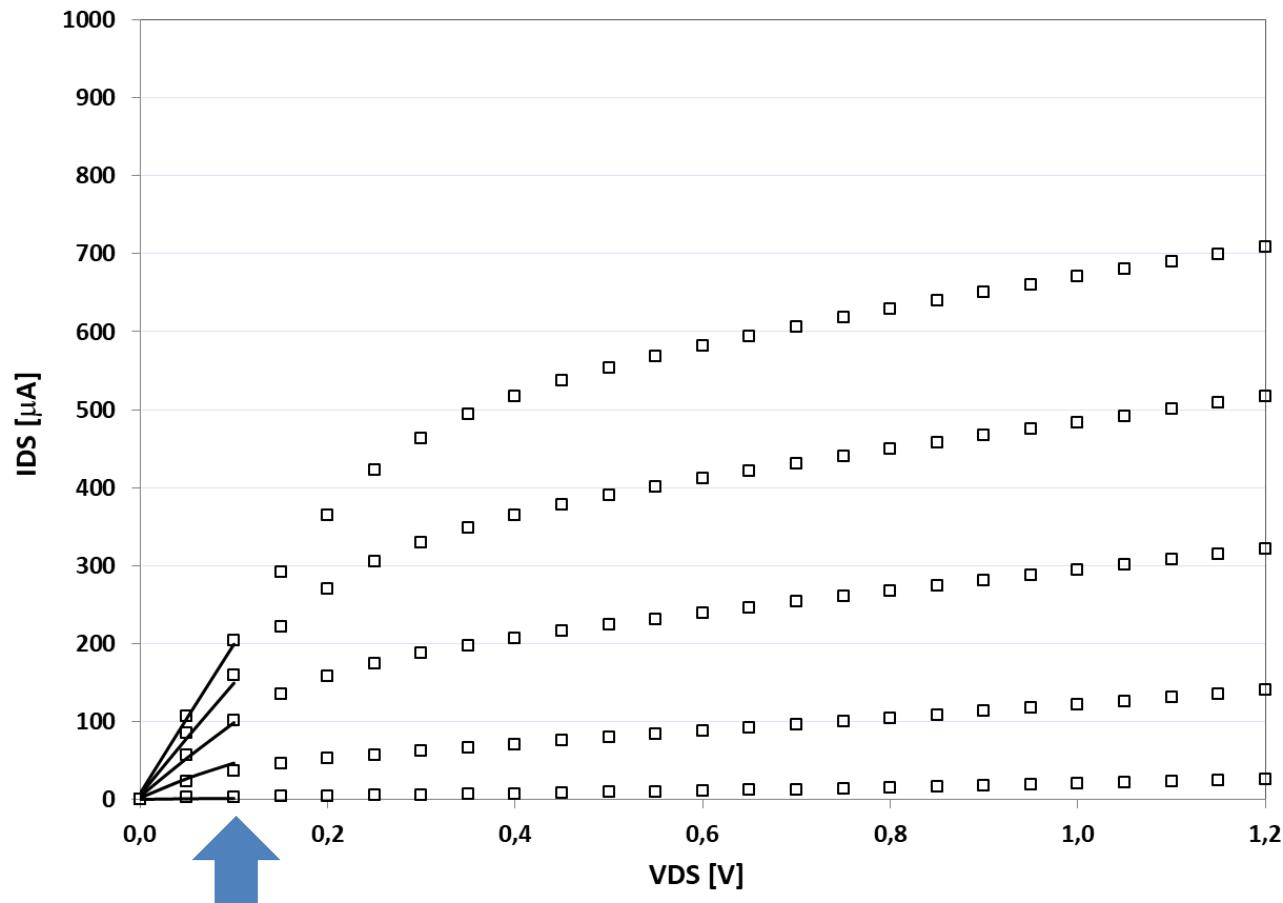
# How good is my model?

More parameters considering second-order effects must be included for fitting model to experimental data



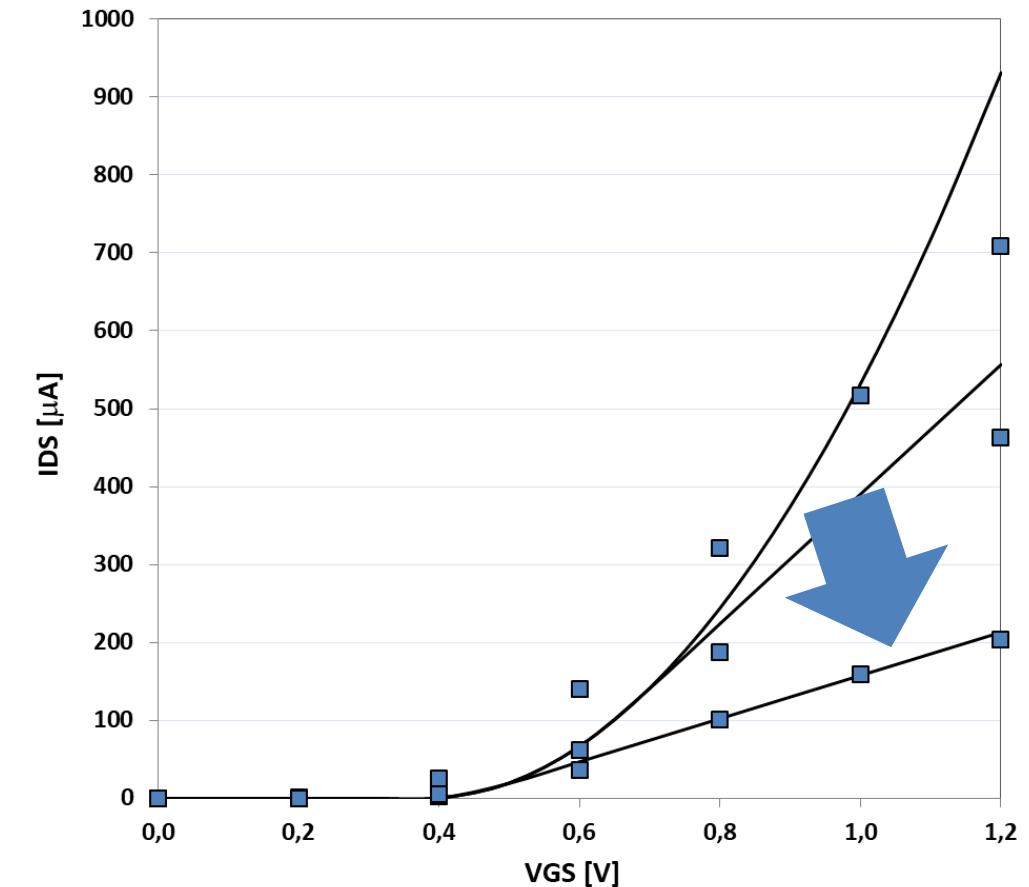
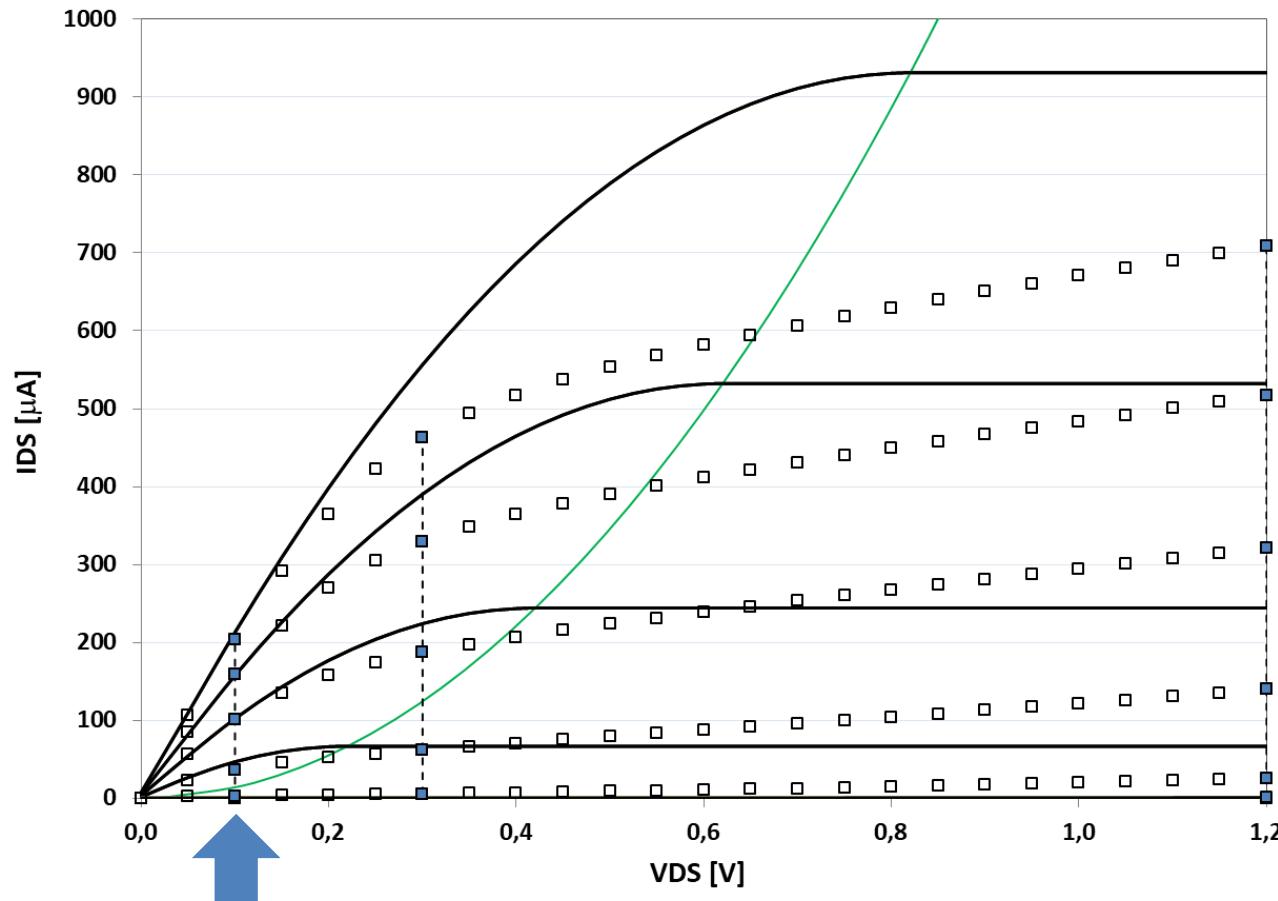
# Determine $k$ and $V_T$ @ $V_{DS}=100$ mV

More parameters considering second-order effects must be included for fitting model to experimental data

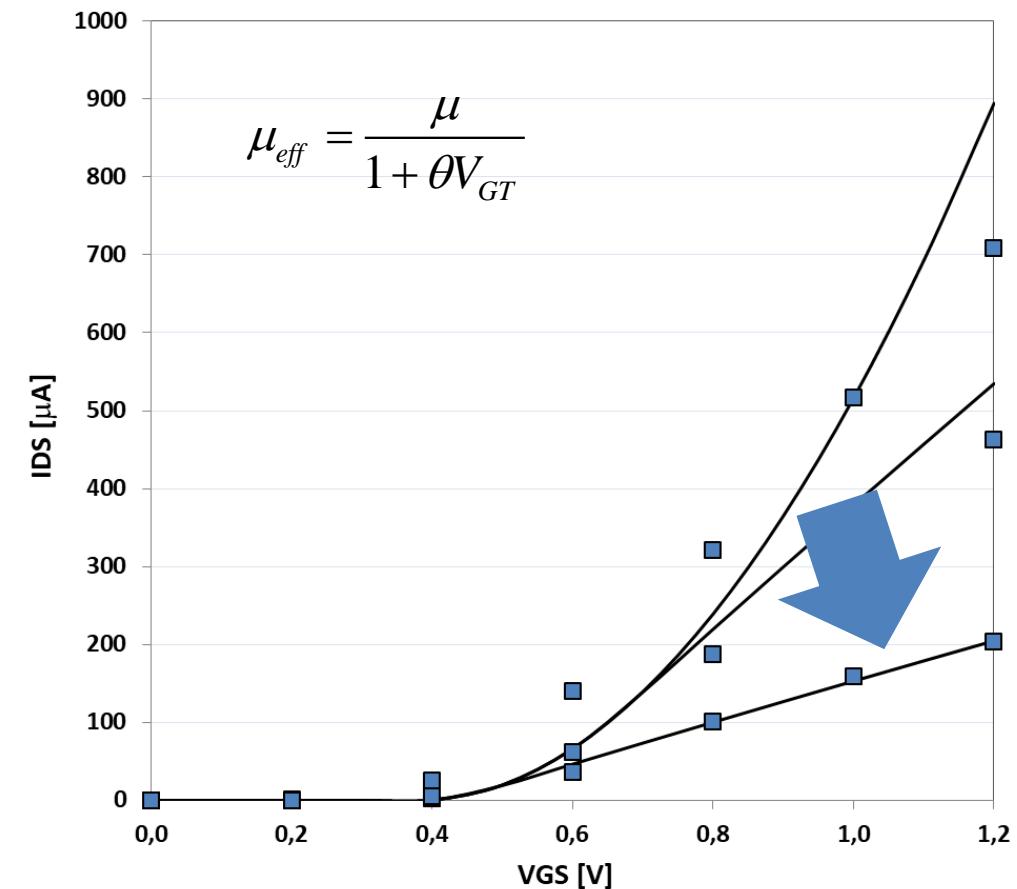
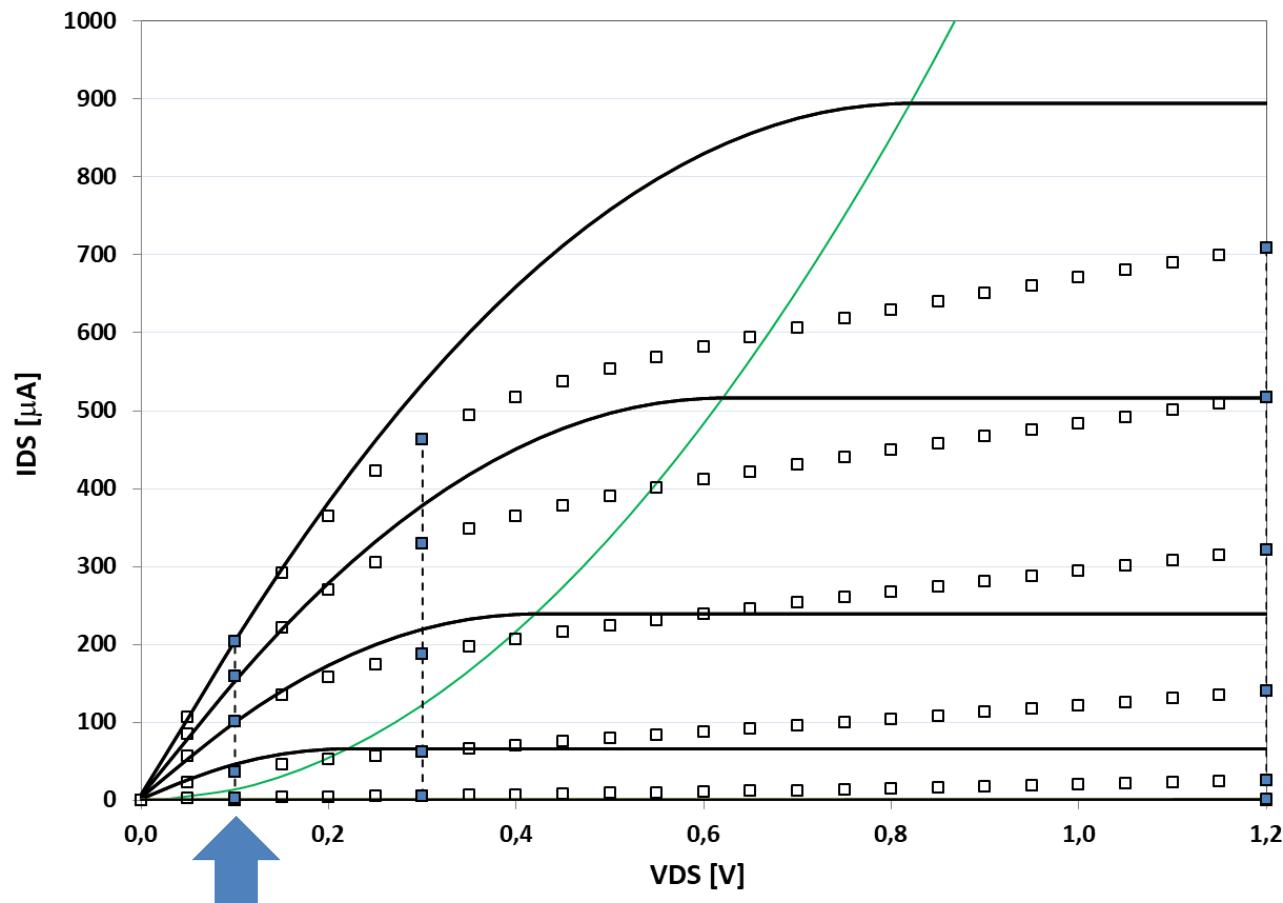


# Determine $k$ and $V_T$ @ $V_{DS}=100$ mV

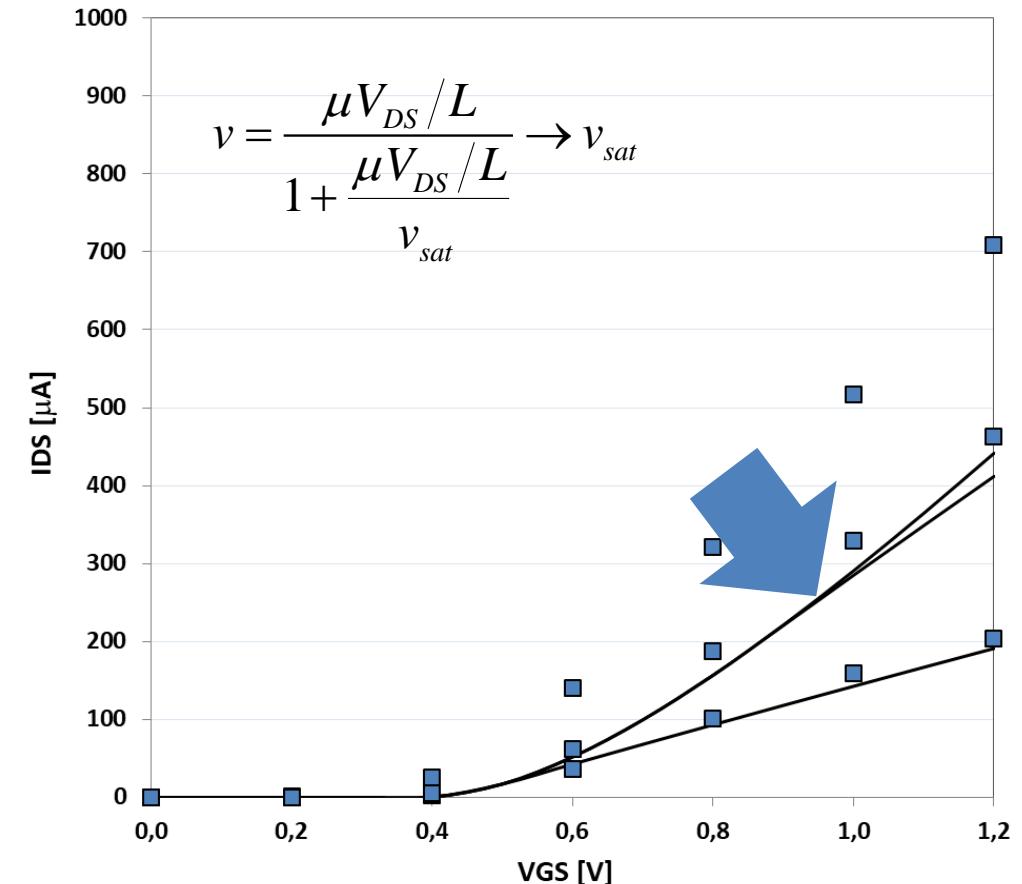
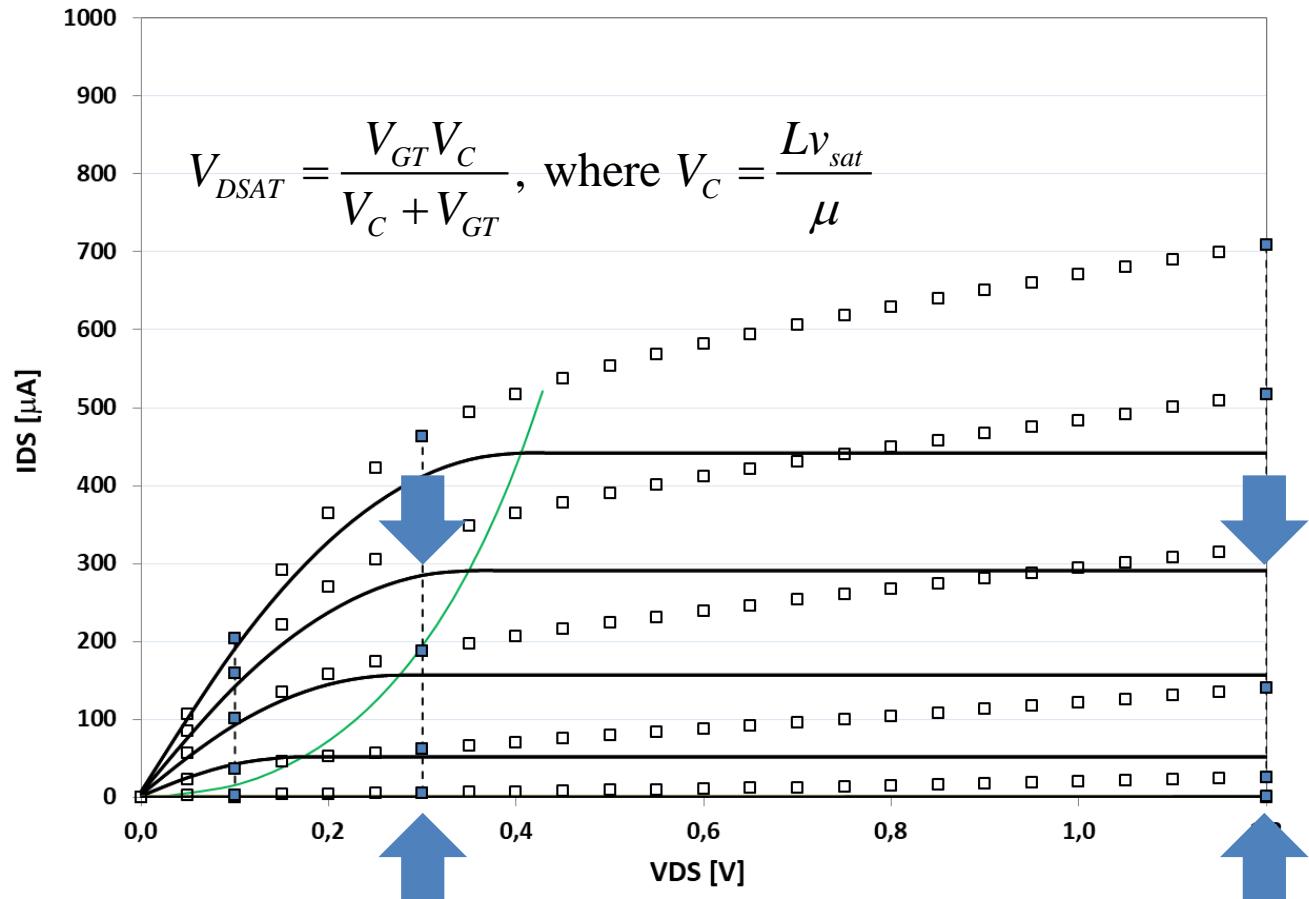
More parameters considering second-order effects must be included for fitting model to experimental data



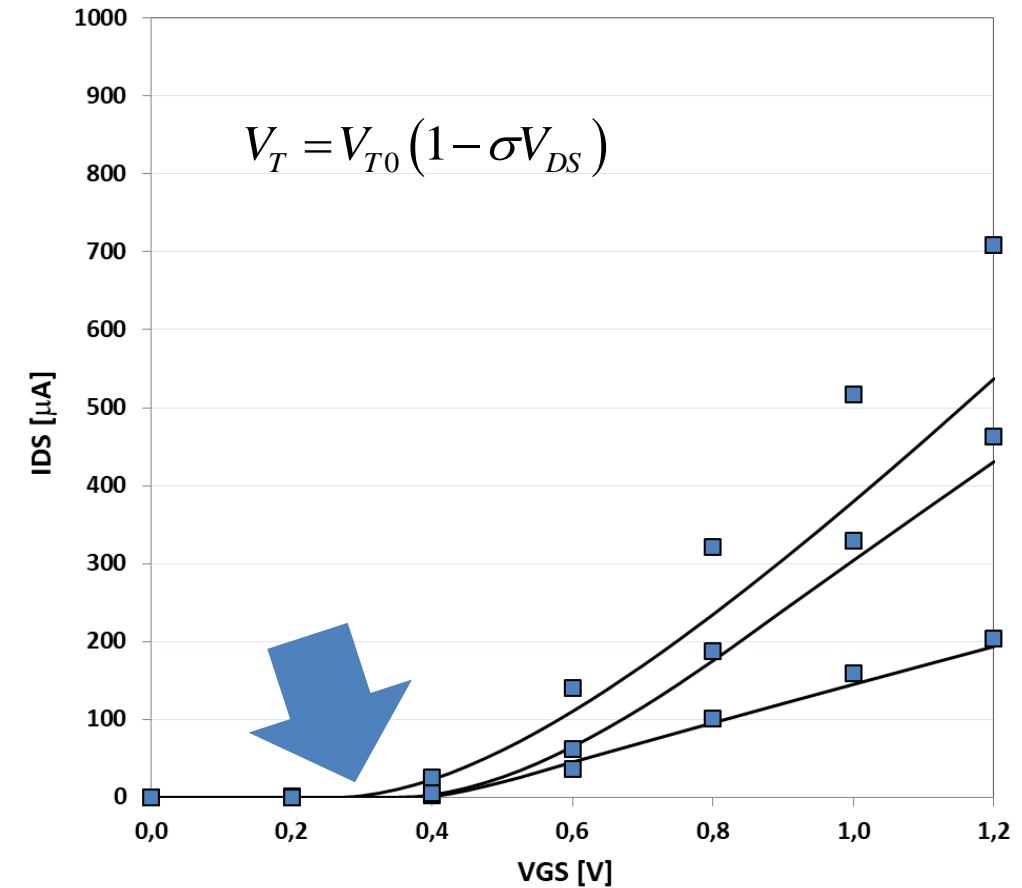
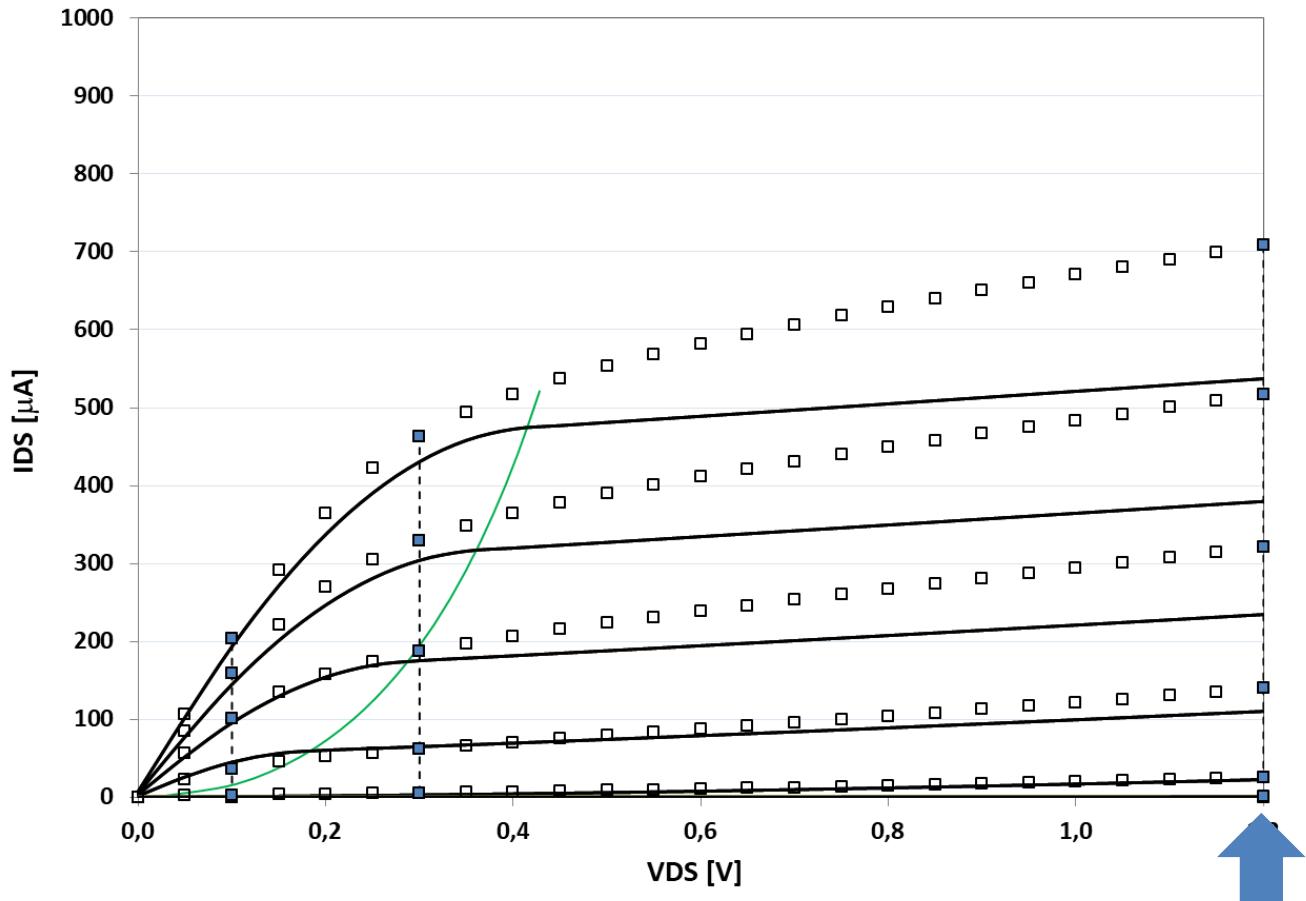
# Include mobility roll-off



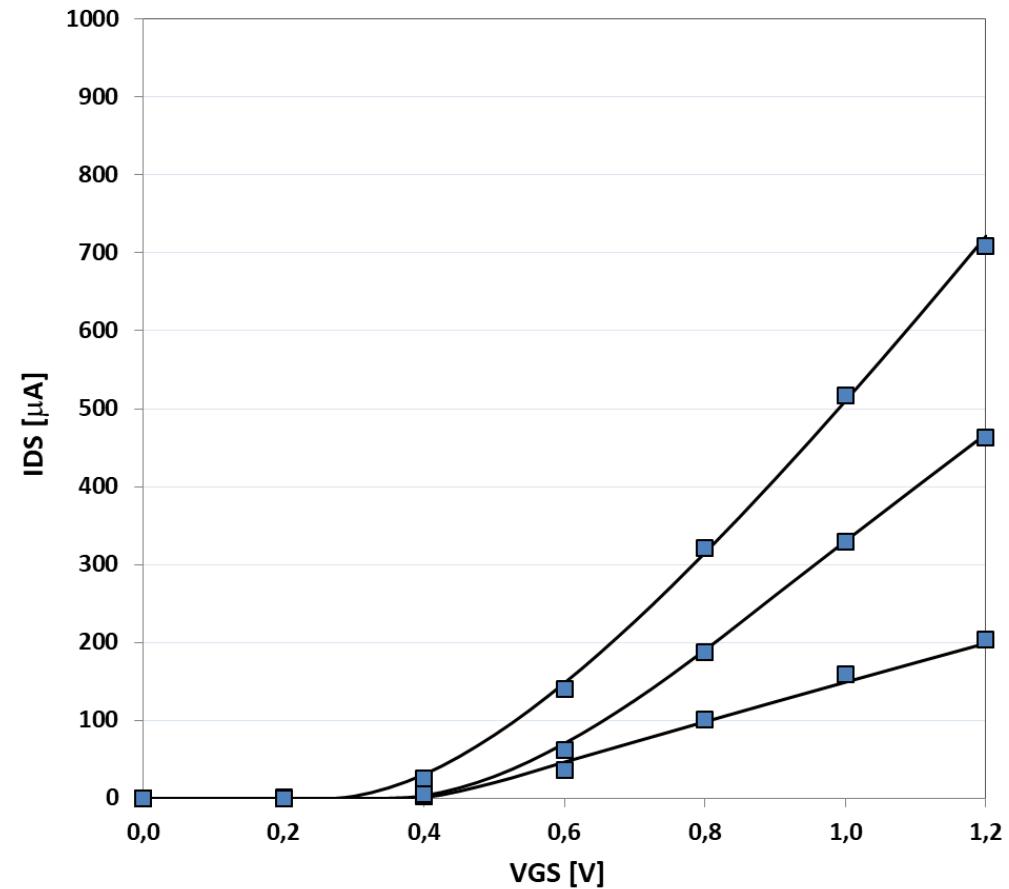
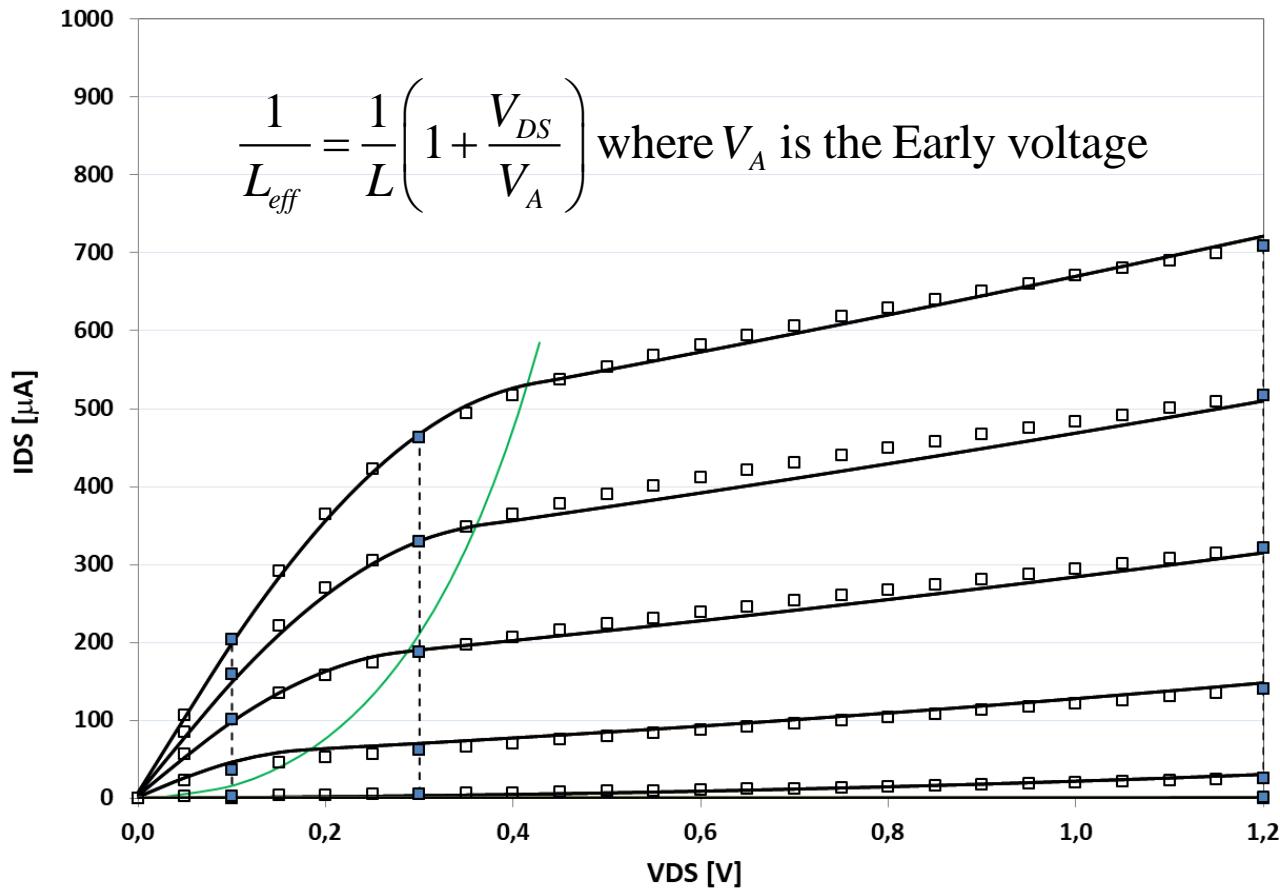
# Consider velocity saturation



# Consider drain-induced barrier-lowering (DIBL)

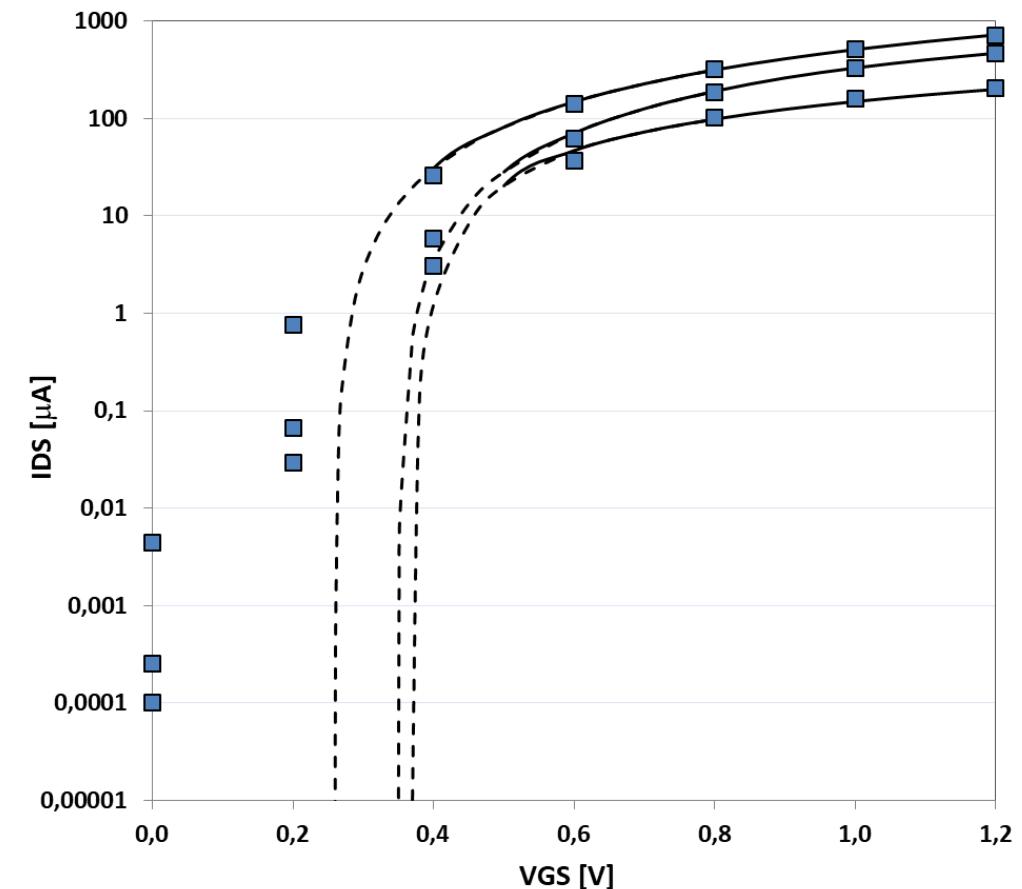
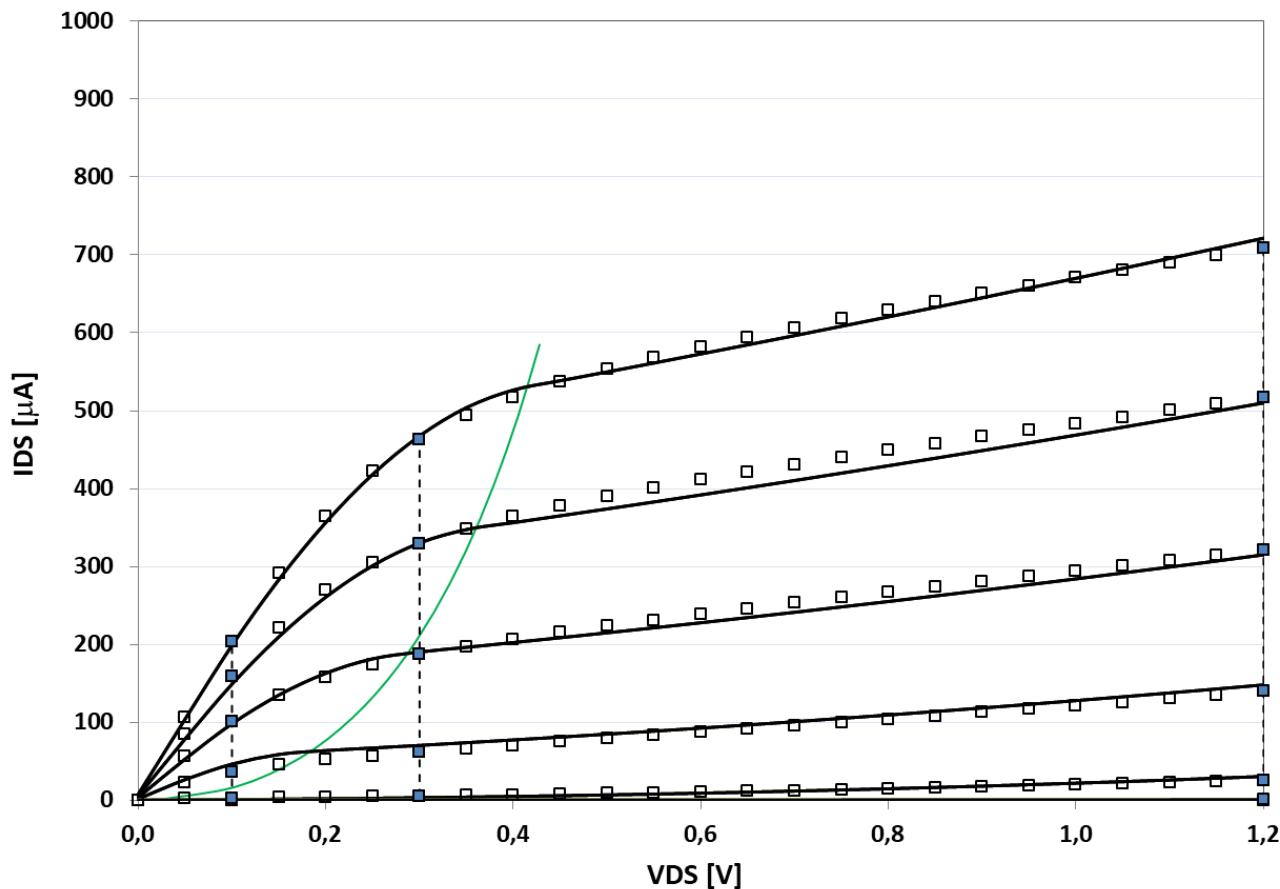


# Consider channel length modulation (CLM)



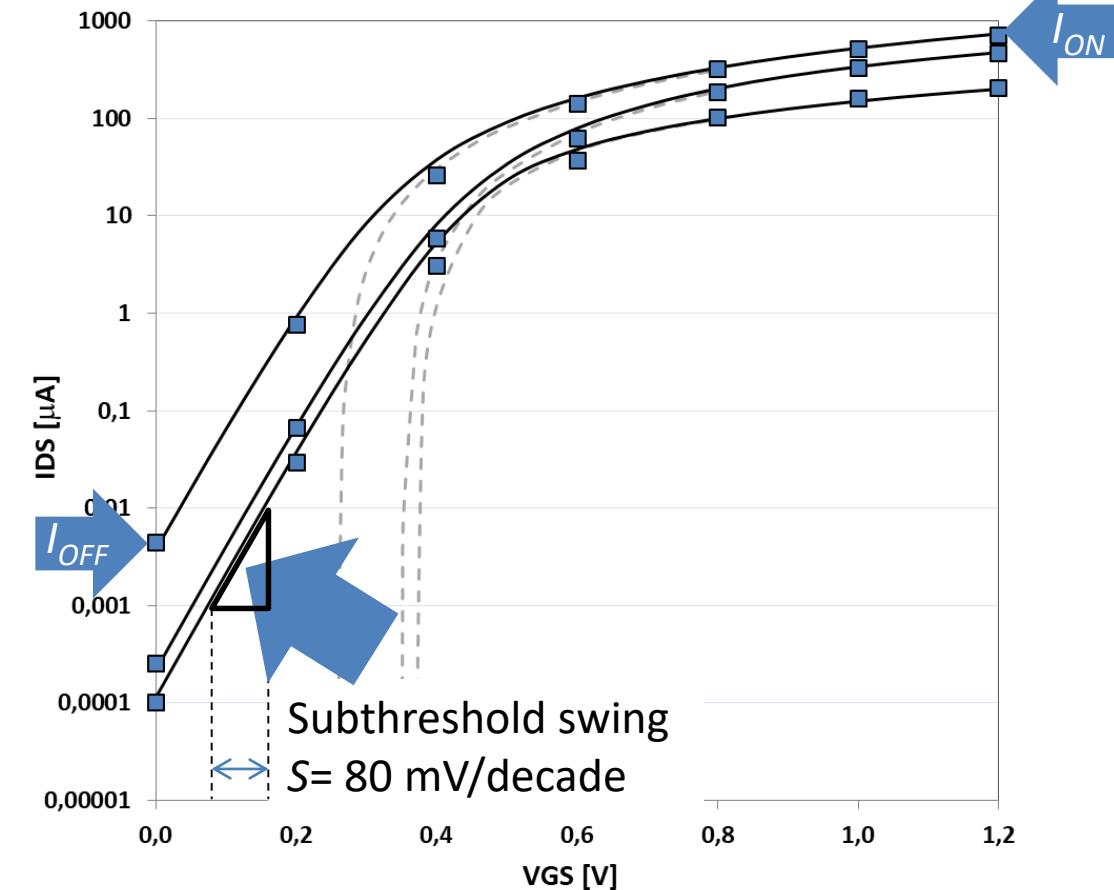
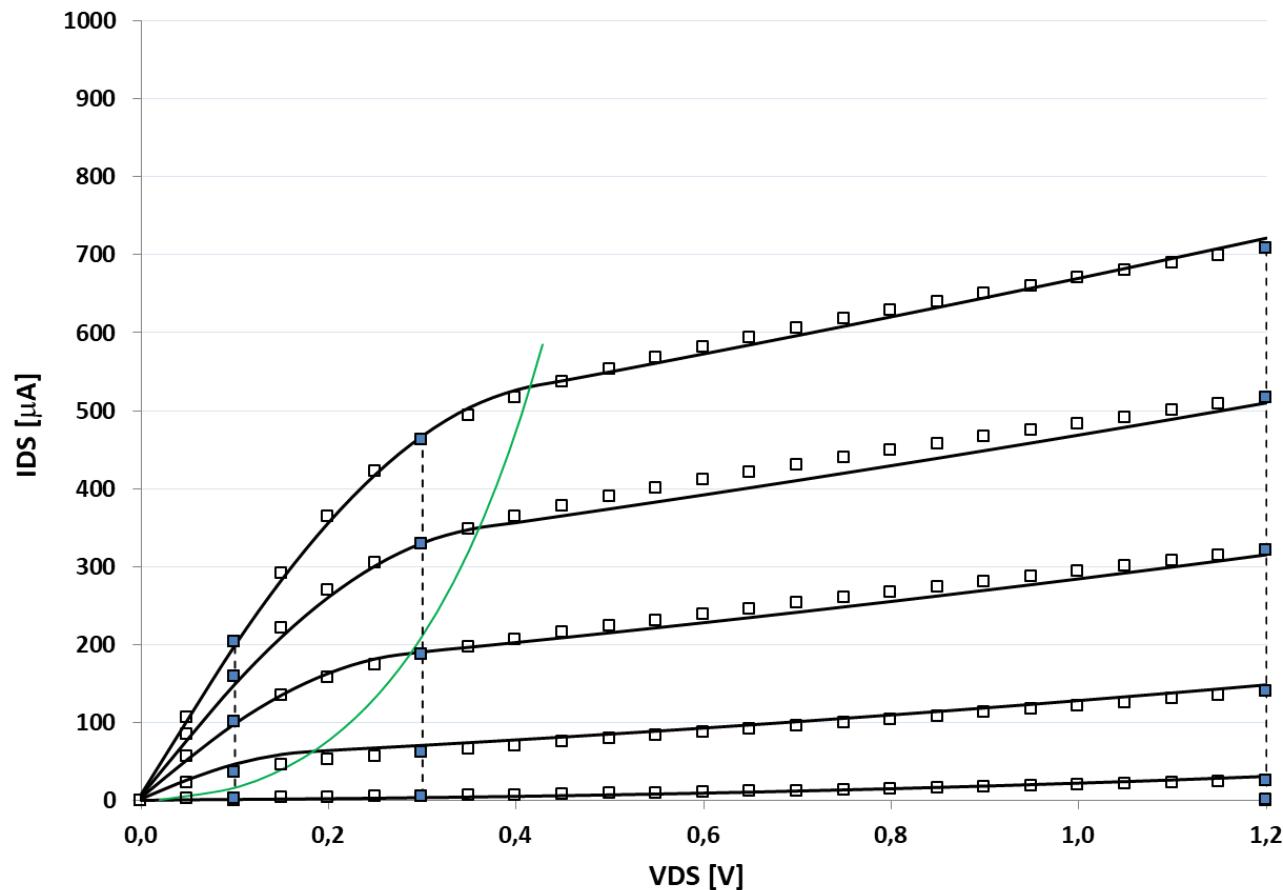
# Subthreshold leakage

Replot transfer characteristic on a semilogarithmic scale!



# Subthreshold leakage

Replot transfer characteristic on a semilogarithmic scale!



# Conclusion

In this lecture, we started considering MOSFET static properties

- Three regions of operation
  - Two ON regions: linear or saturated
  - One OFF region: subthreshold

In second half of lecture we also considered dynamic properties

- The intrinsic gate capacitance
- The extrinsic, or parasitic drain capacitance

We came up with a two-port model including both static circuit elements (resistor or current-source), and dynamic elements, i.e. capacitances!